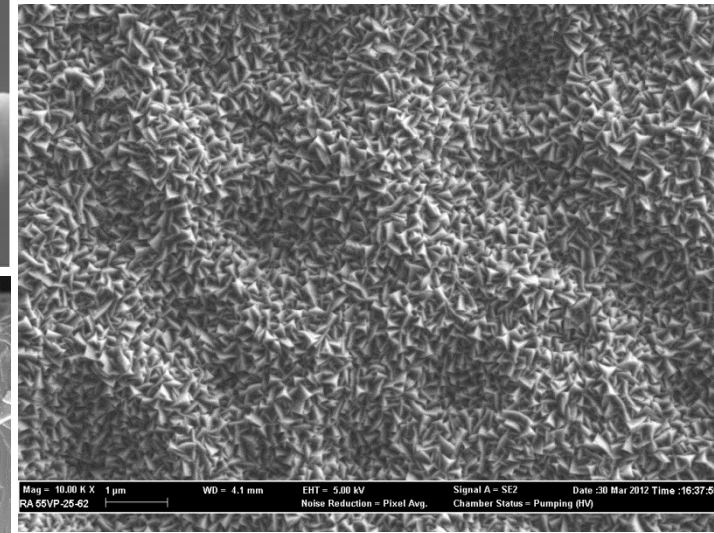
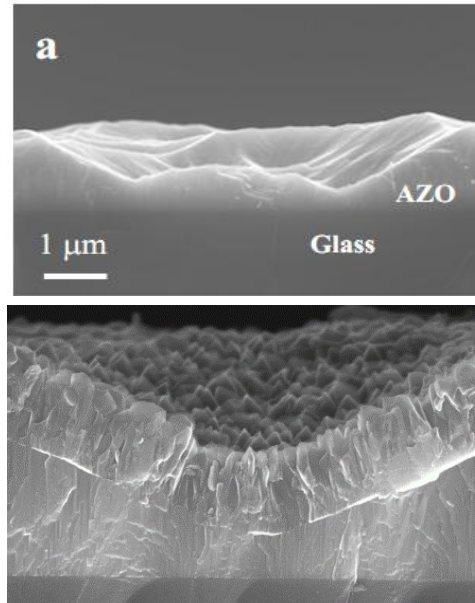
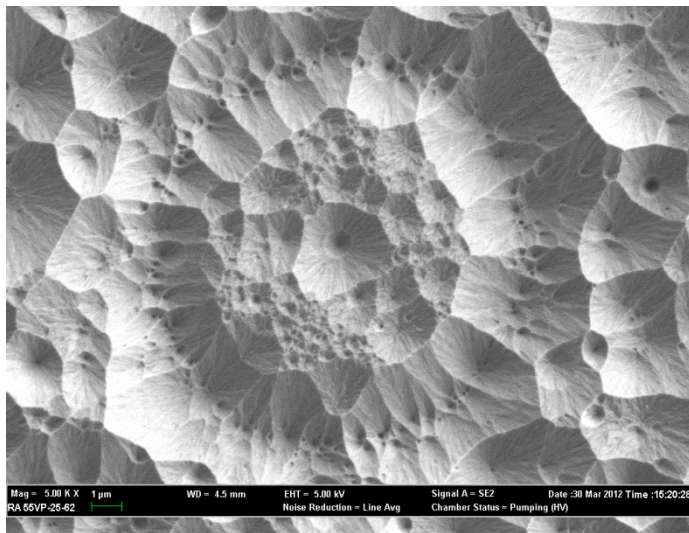




南开大学
Nankai University

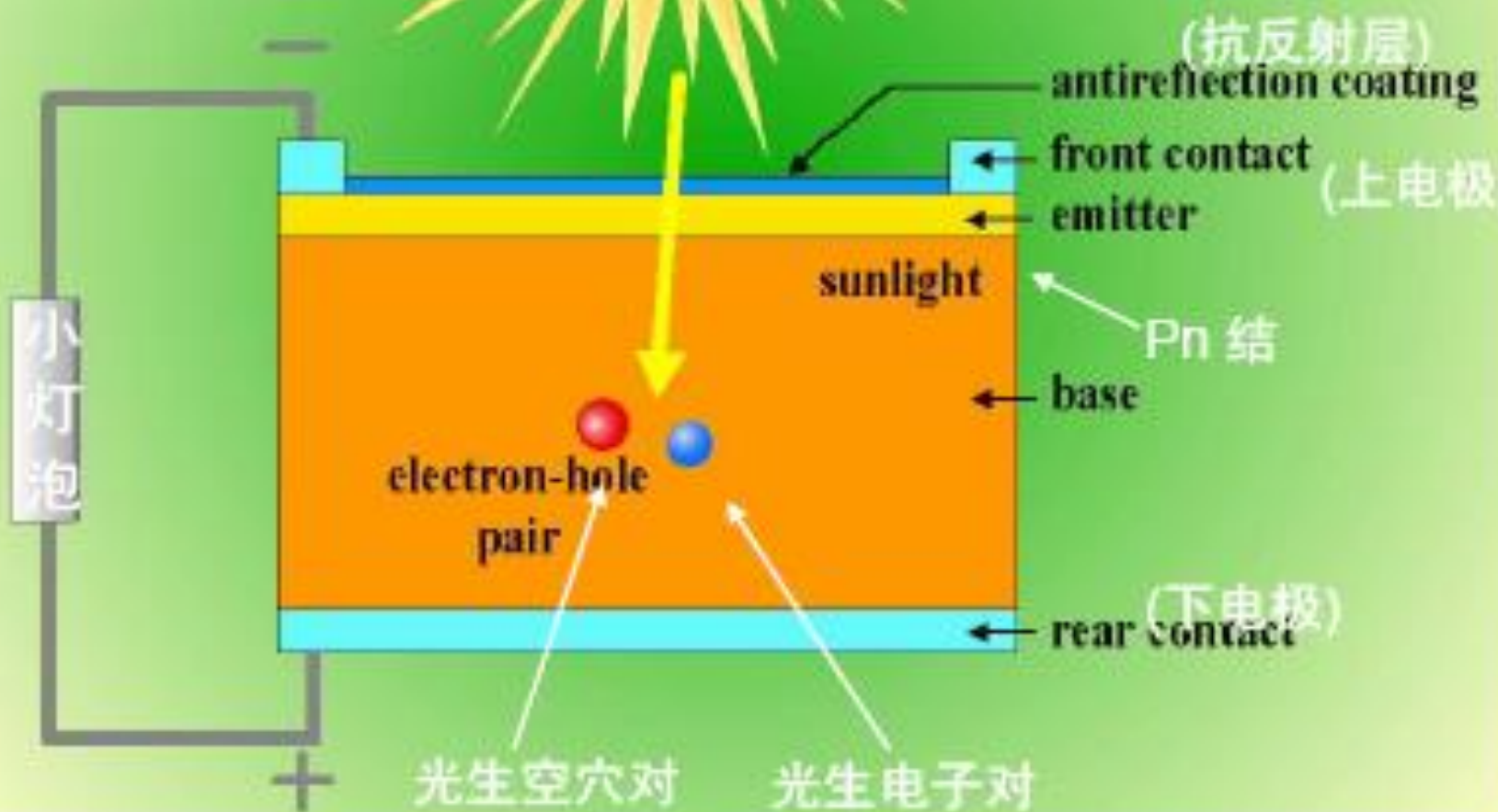
Institute of photo-electronics thin film
devices and technique

Research on high efficiency and low cost thin film silicon solar cells



Xiaodan Zhang
Nankai University

2013 China-America Frontiers of Engineering, May 15-17, Beijing, China





南开大学 Nankai University

Institute of photo-electronics thin film
devices and technique



(Sonnen, Bayern, Germany)





南开大学
Nankai University

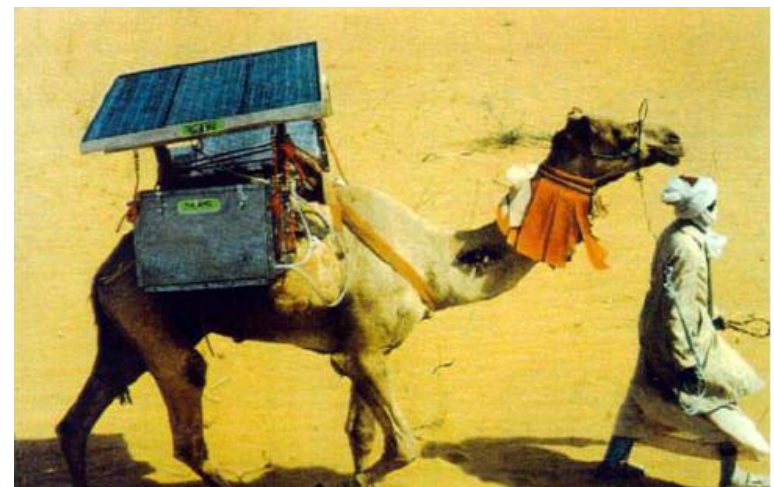
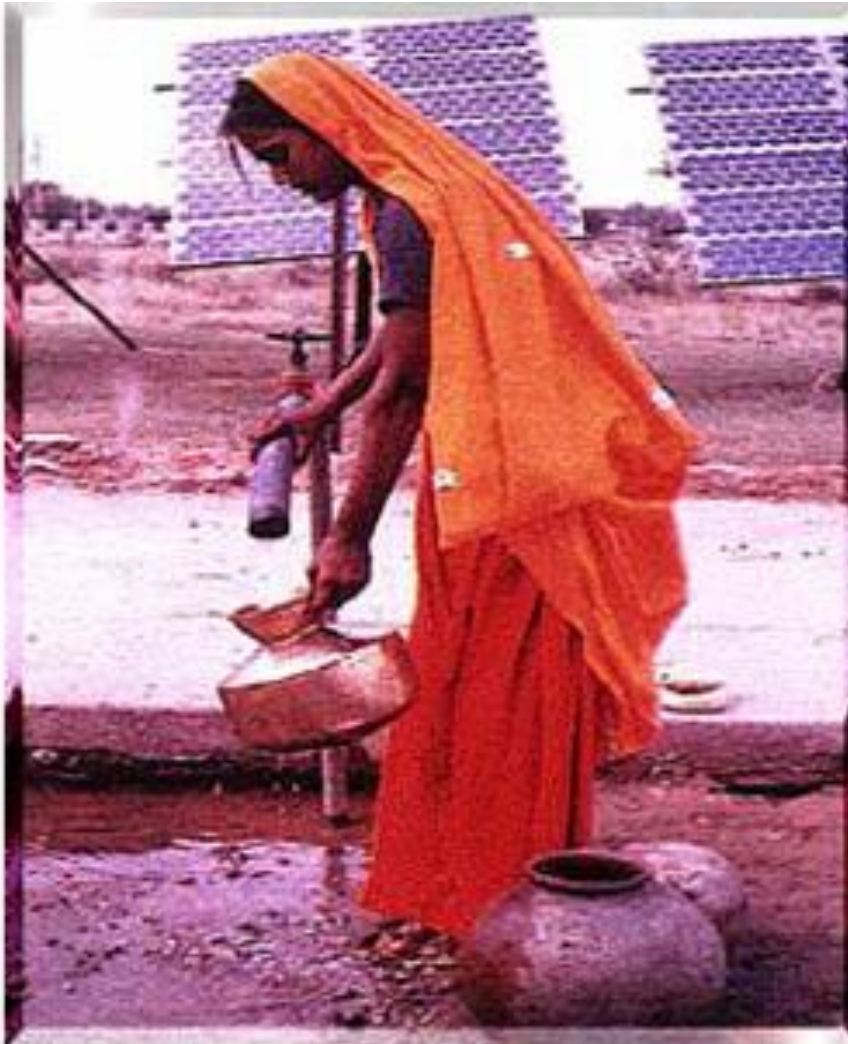
Institute of photo-electronics thin film
devices and technique





南开大学
Nankai University

**Institute of photo-electronics thin film
devices and technique**





南开大学
Nankai University

**Institute of photo-electronics thin film
devices and technique**

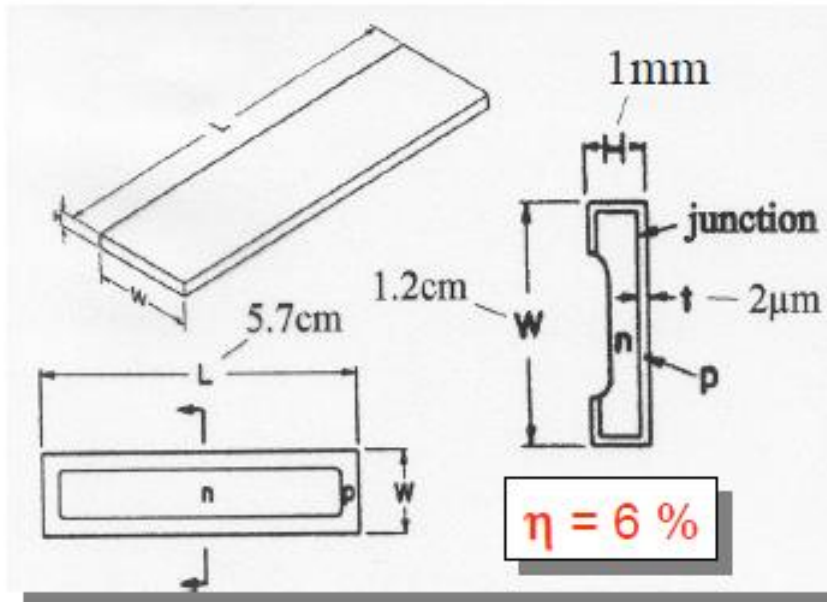




1954: The Birth of Solar Photovoltaics

A New Silicon p - n Junction Photocell for Converting Solar Radiation into Electrical Power

D. M. CHAPIN, C. S. FULLER, AND G. L. PEARSON
Bell Telephone Laboratories, Inc., Murray Hill, New Jersey
(Received January 11, 1954)





1. **Crystalline silicon solar cells**

- Mono-crystalline and poly-crystalline solar cells



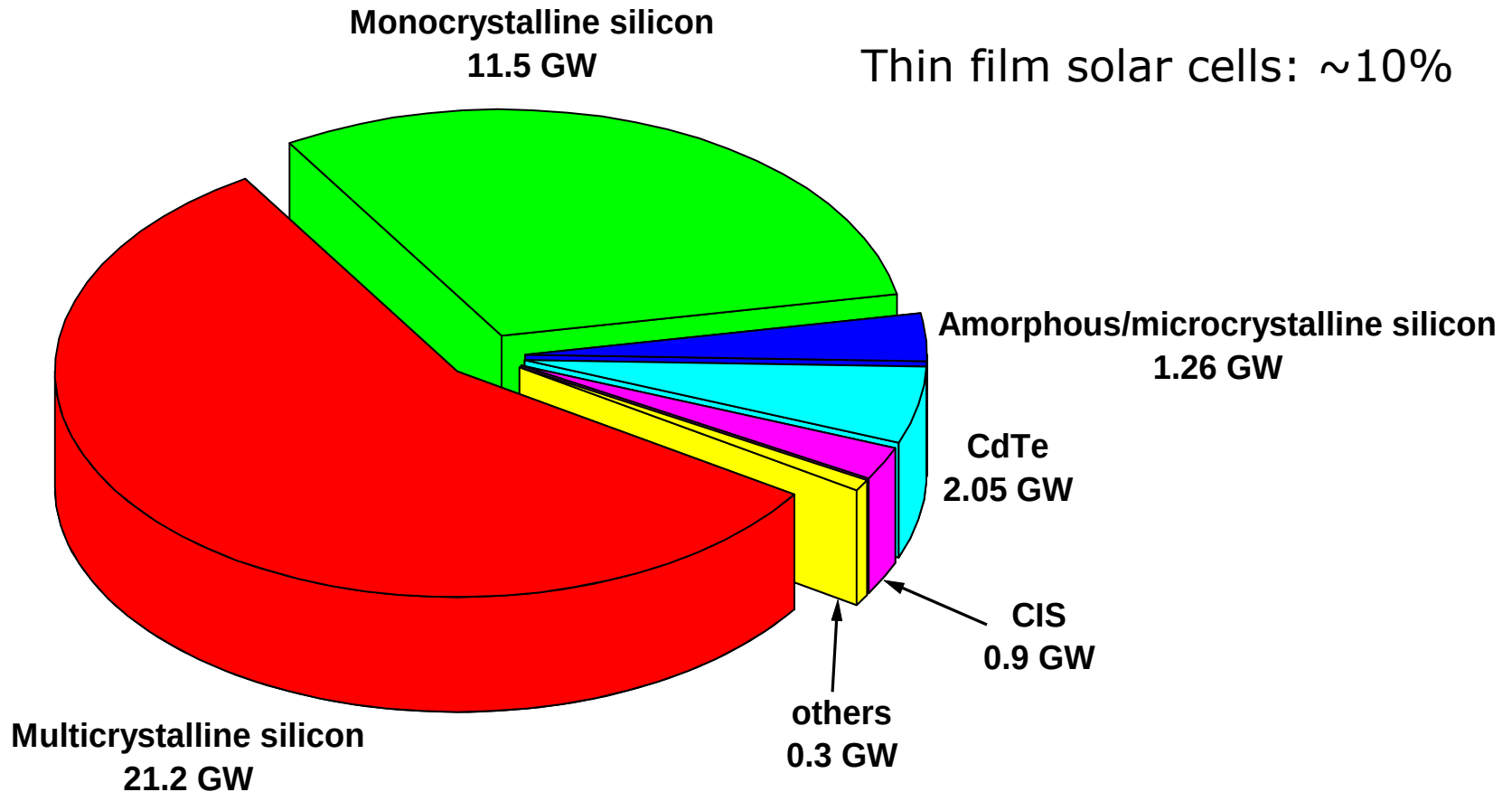
2. **Thin film solar cells**

- Silicon-based thin film solar cells
- Copper Indium Gallium Selenide solar cells (CIGS)
- CdTe solar cells
- Dye sensitized solar cell (DSC)



3. **Concentrated solar cells**





2011 Total Production : 37 GW



南开大学
Nankai University

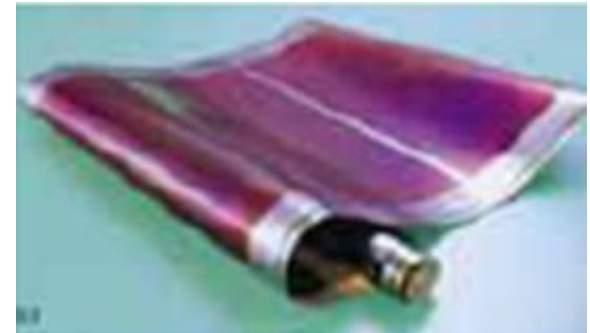
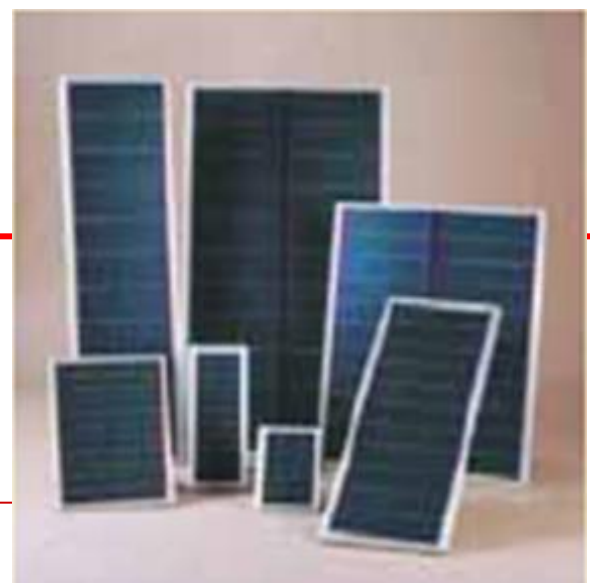
Thin film silicon solar cells

Advantages:

- No materials limited
- Low deposited temperature ($<200^{\circ}\text{C}$)
- Deposited on different substrates

Disadvantages:

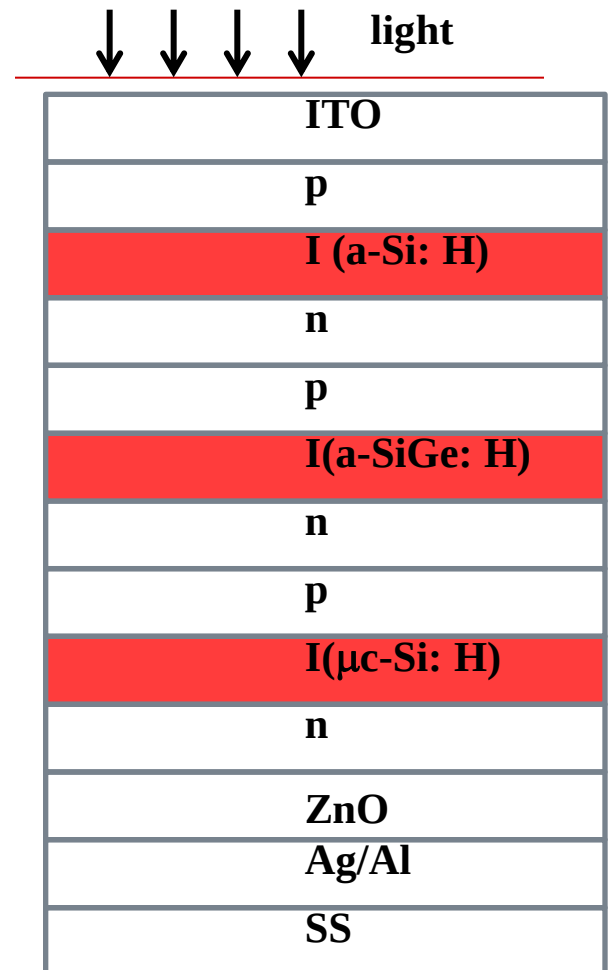
- Low conversion efficiency
- Light induced degradation efficiency





Thin film Silicon solar cell structures: substrate configuration

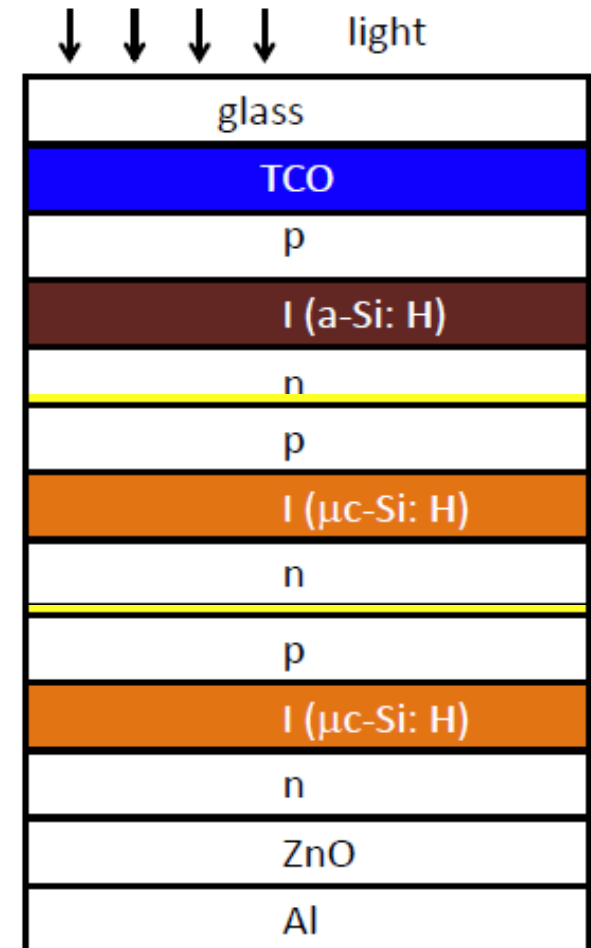
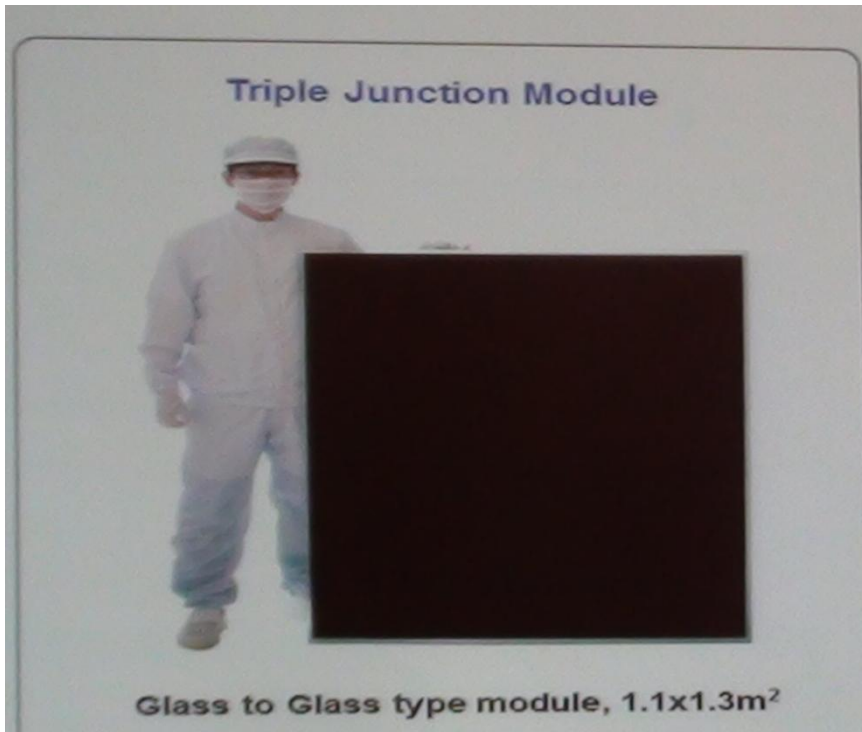
1. Initial 16.3% efficiency has been achieved using **a-Si:H/a-SiGe:H/ $\mu\text{c-Si:H}$** structure .
-----nip





Thin film Silicon solar cell structures: superstrate configuration

2. Stable 13.44% efficiency has been achieved using **a-Si:H** / $\mu\text{c-Si:H}$ / $\mu\text{c-Si:H}$ structure .-
-----pin





Thin film silicon PV technology

Target: Low cost and high conversion efficiency

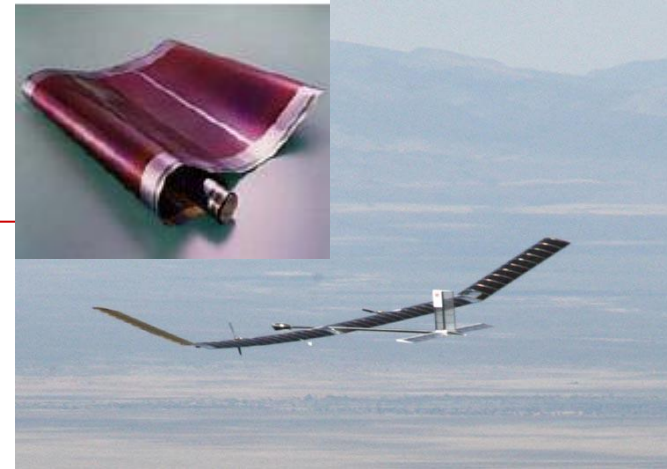
1. Key issue: increase efficiency

- Multi-junction for full use of solar spectrum
- New materials
- Advanced light trapping
- New structures
- New concepts
-

2. Key issue: reduce cost

- High deposition rate
- High stable efficiency
- Single chamber deposition
- Suitable large area
-

3. Summary and outlook





1. Key issue: increase efficiency

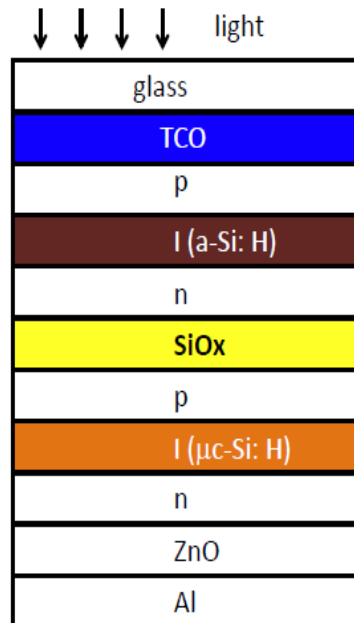
New materials: Amorphous and microcrystalline silicon alloys

Deposition technique:

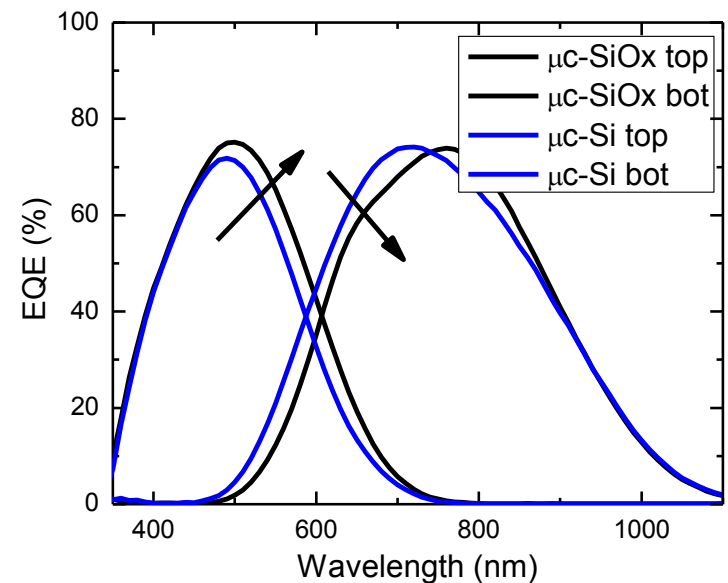
- PECVD, VHF-PECVD

Applications:

- Doped layers
- Intermediate reflectors
- Index matching layers
-



For example: $\mu\text{c-SiOx}$





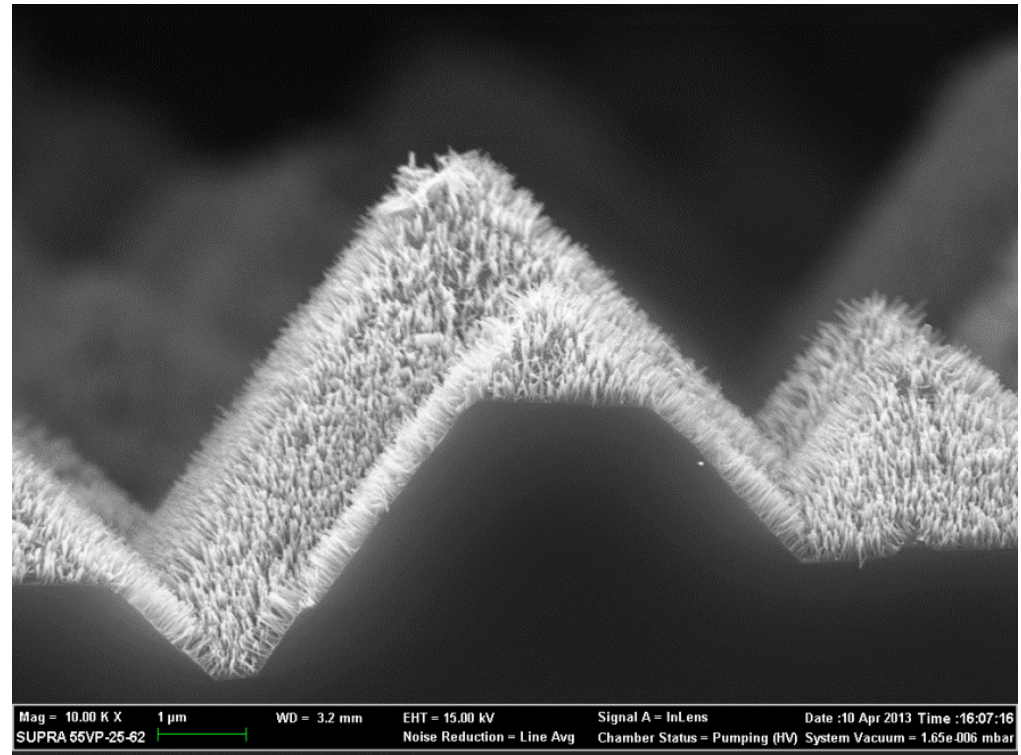
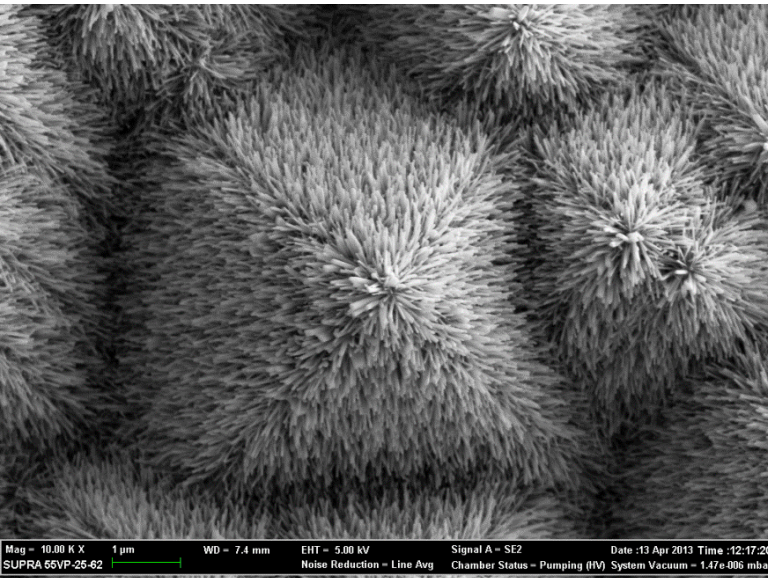
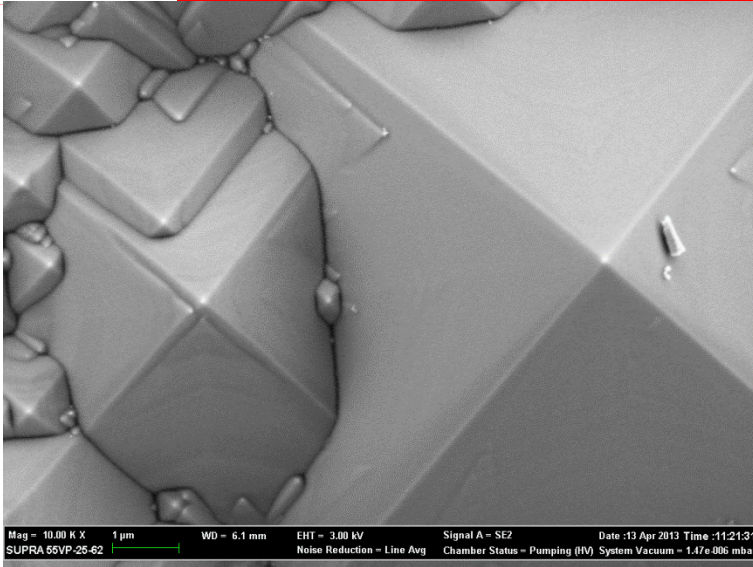
Light trapping: Trap light inside the absorber layer

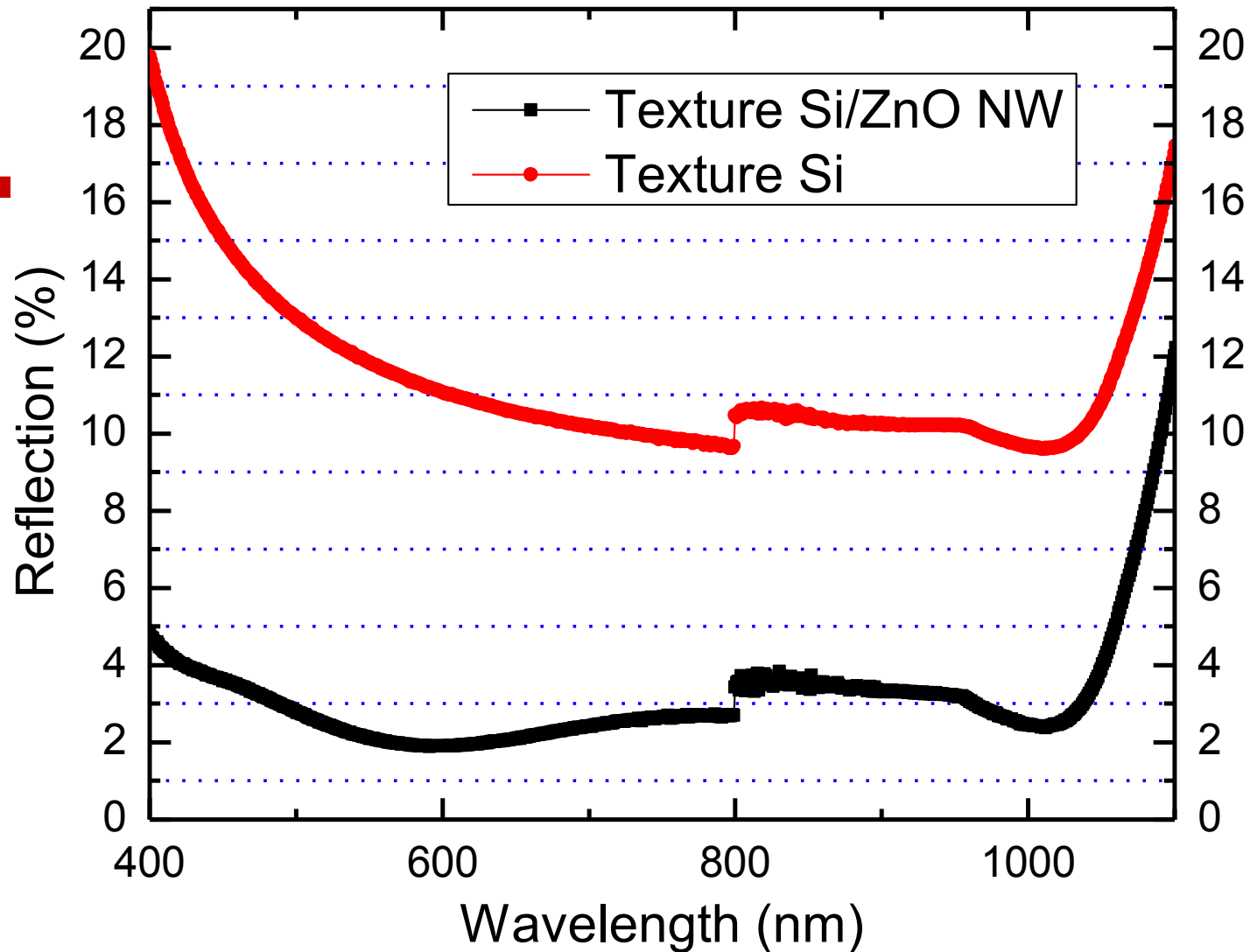
Approaches:

- Effective light in-coupling at the front side
 - ✓ **Nano-structured ARC**
- Scattering at rough interfaces
 - ✓ **Broad band light scattering**
- Reflection at the back side
 - ✓ **Random structure**
 - ✓ **Periodic structure**



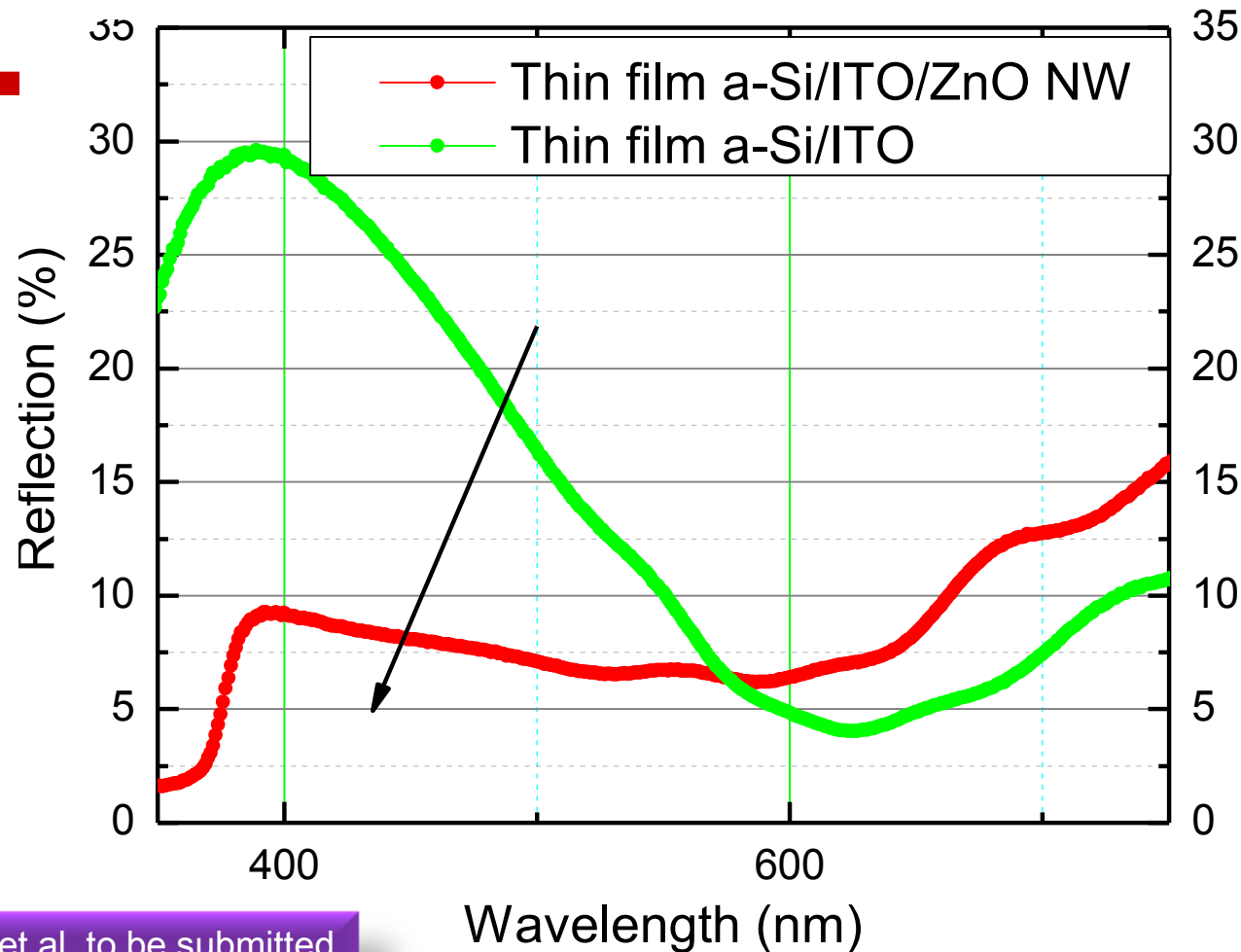
ZnO NW :







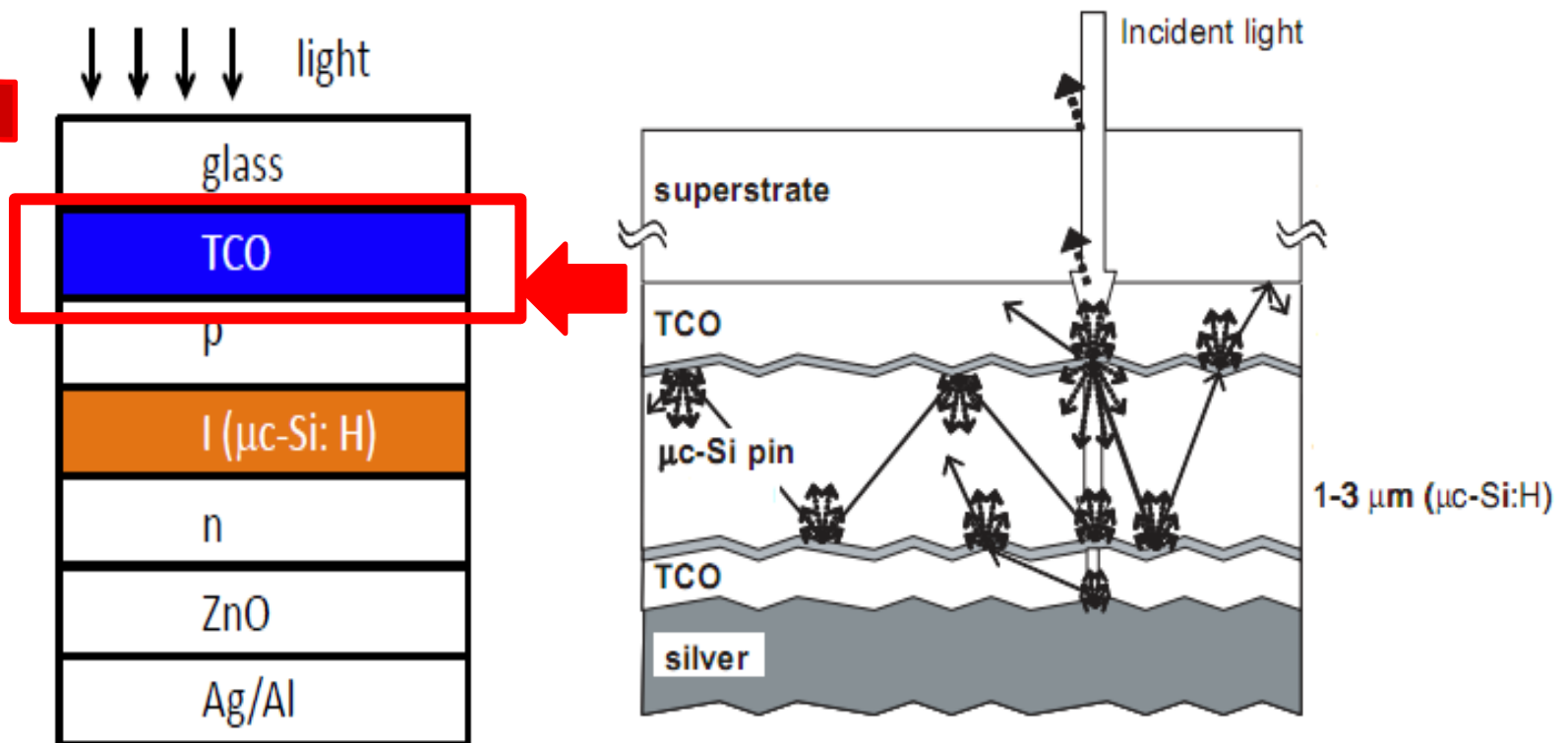
ZnO NW : amorphous silicon





● Scattering at rough interfaces

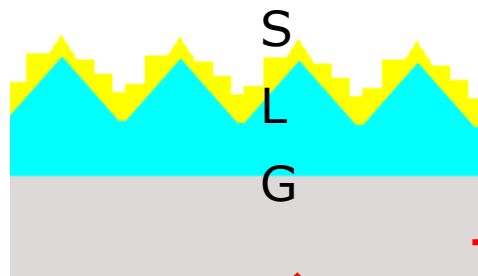
- ✓ To scatter the incident light for effective light trapping
- ✓ To increase the short circuit current density (J_{sc}) in the solar cells.



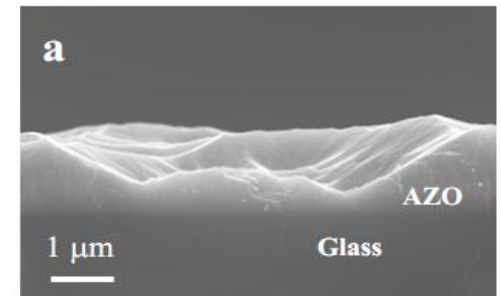
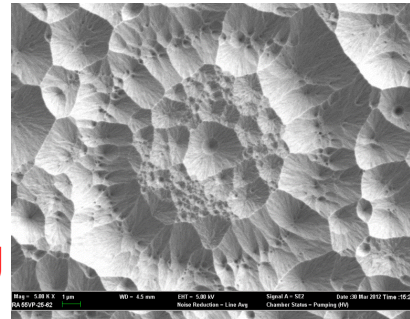


- Scattering at rough interfaces

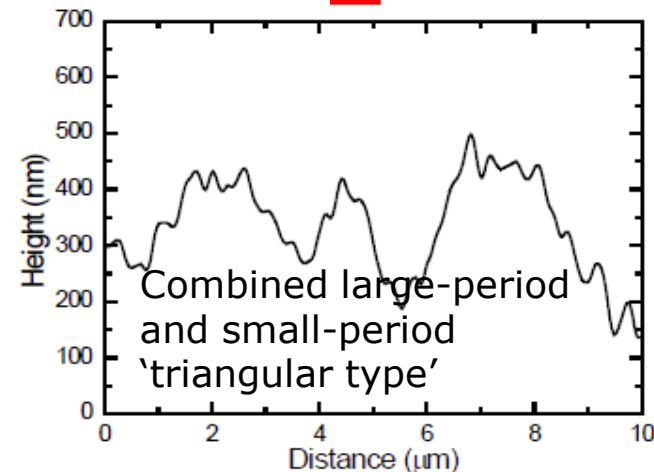
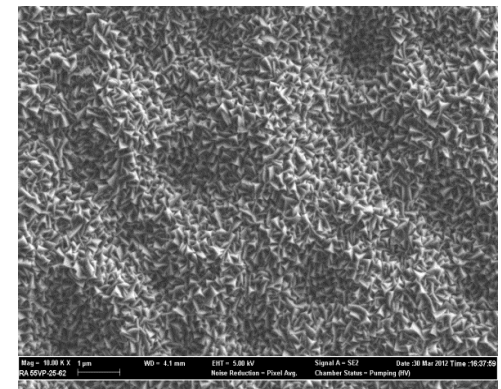
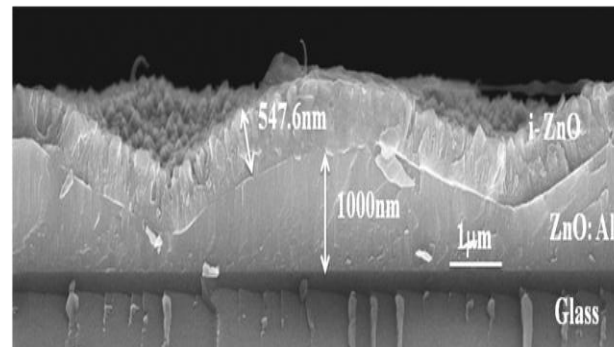
✓ **Broad band light scattering: double 'period' structure--Sputtering+ MOCVD**



Sputtering
+ Wet etching



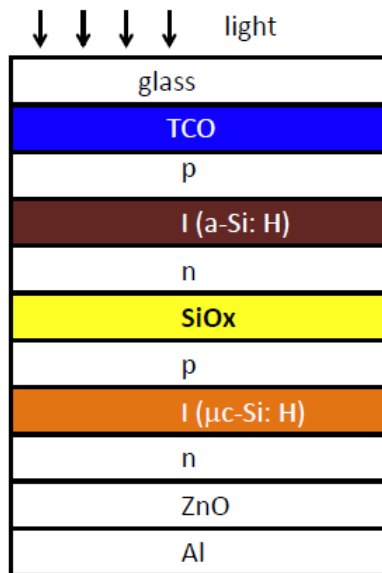
MOCVD



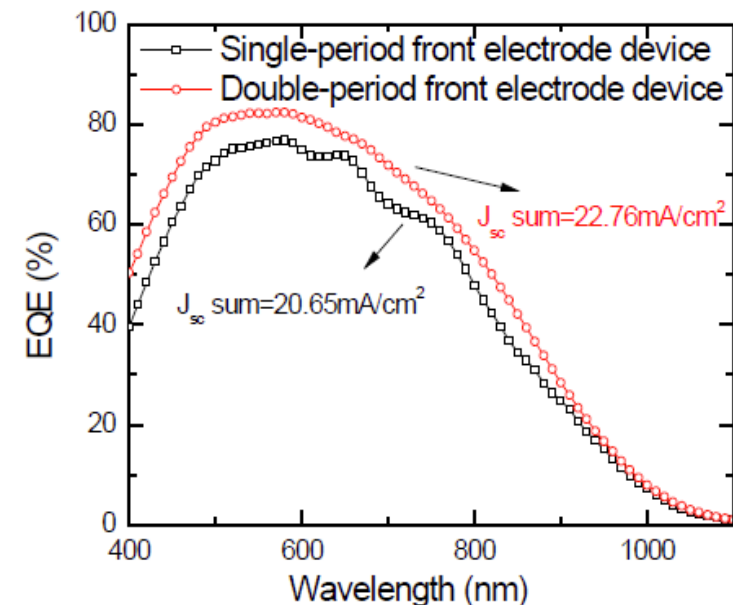
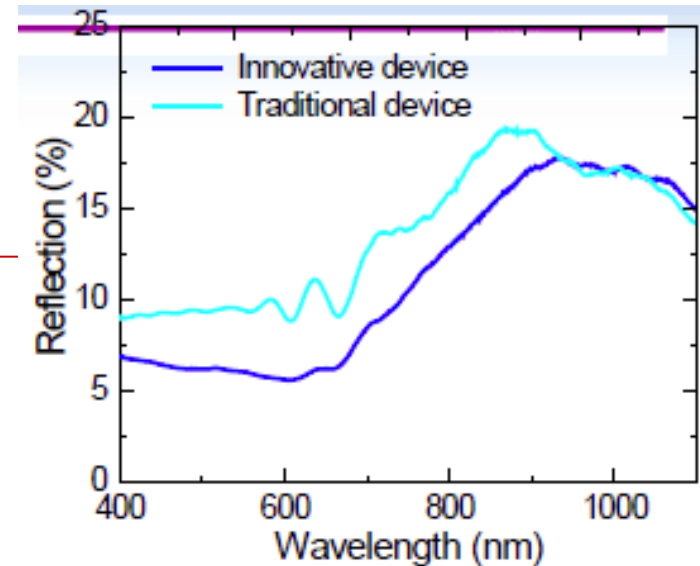
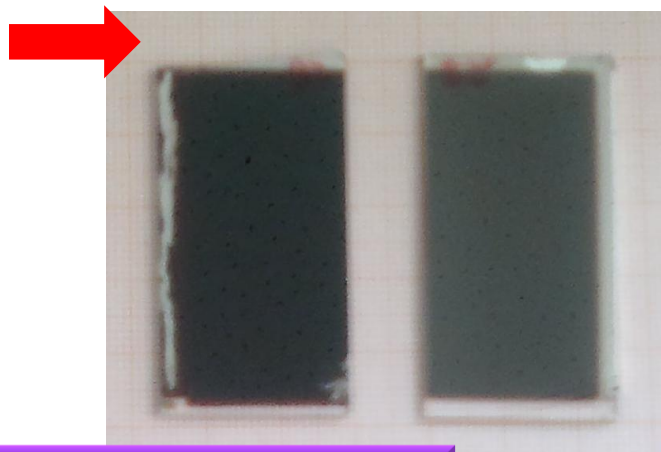


Micromorph tandem solar cells with the innovative front electrode:

- Looks black
- Low reflection
- High current density

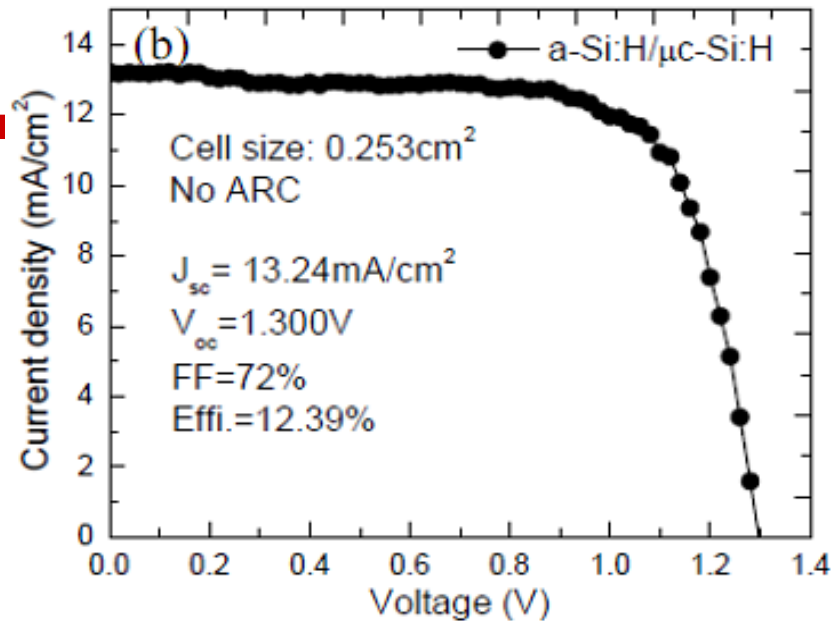
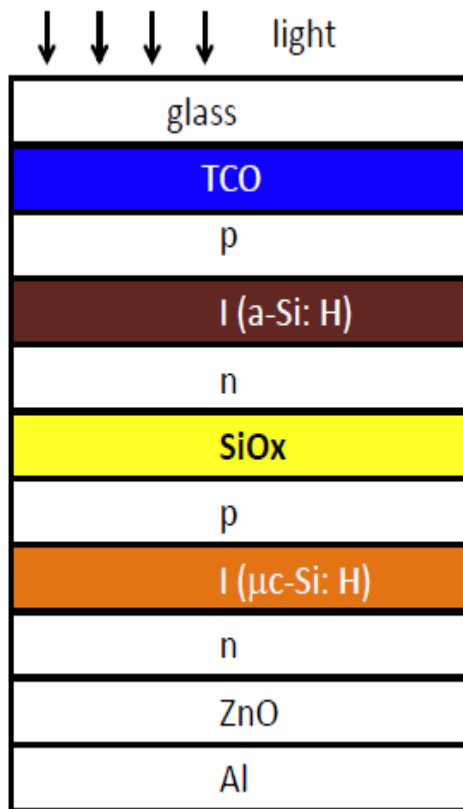


Innovative Traditional





a-Si/ μ c-Si tandem solar cells



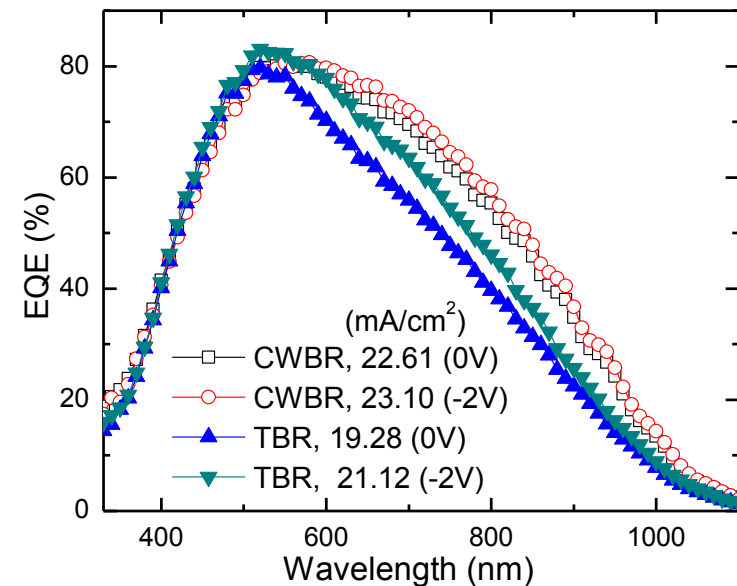
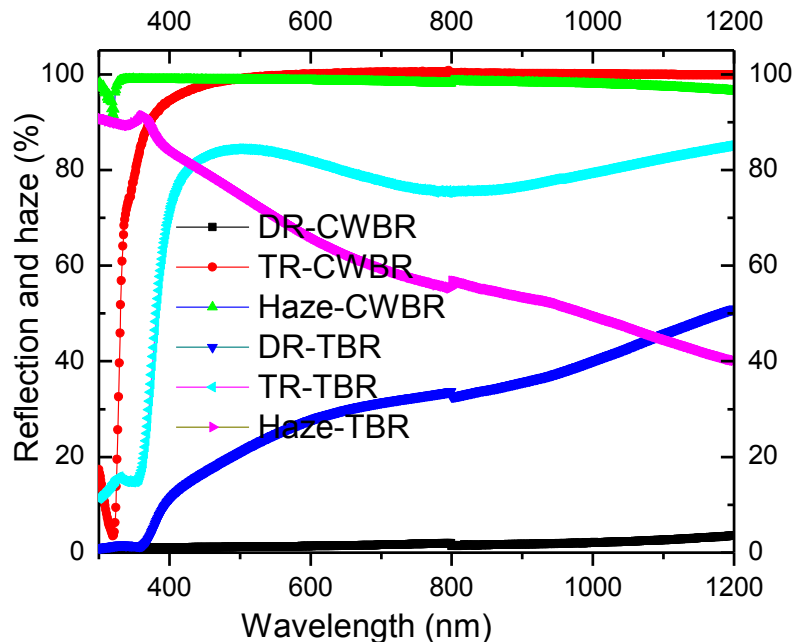
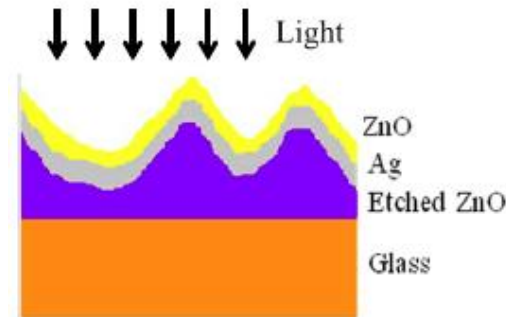
- Optimization of microcrystalline silicon solar cells
- Incorporation of n type SiO_x—Two-phase structure
- Front transparent conductive oxide



● Reflection at the back side

- ✓ Random structure
- ✓ Periodic structure

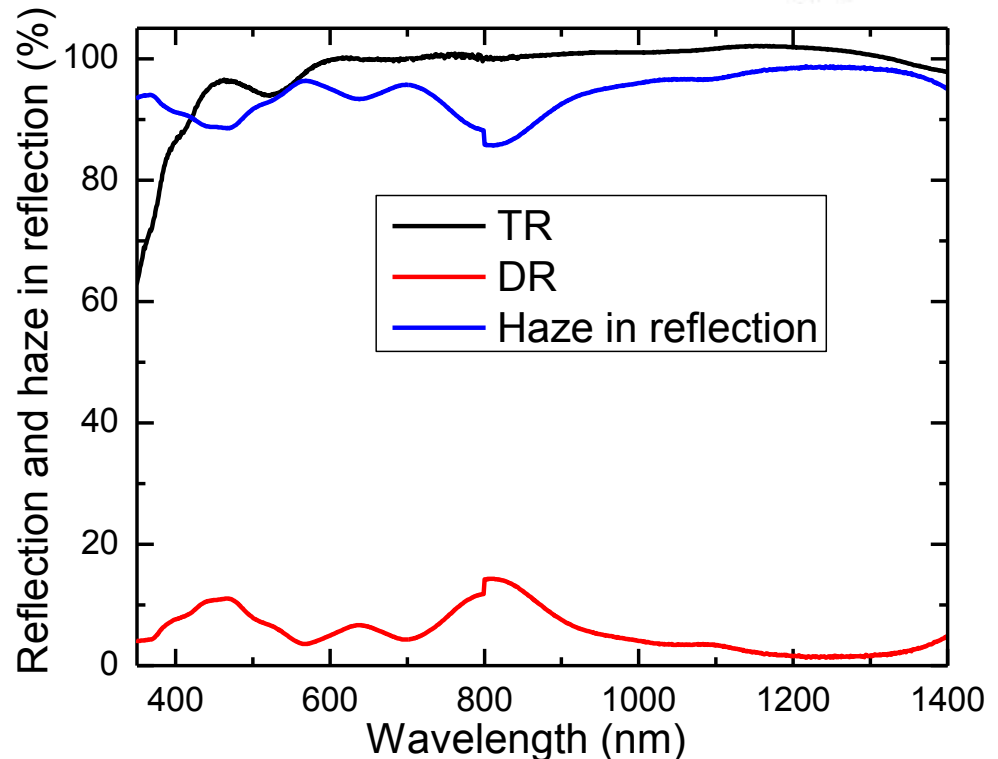
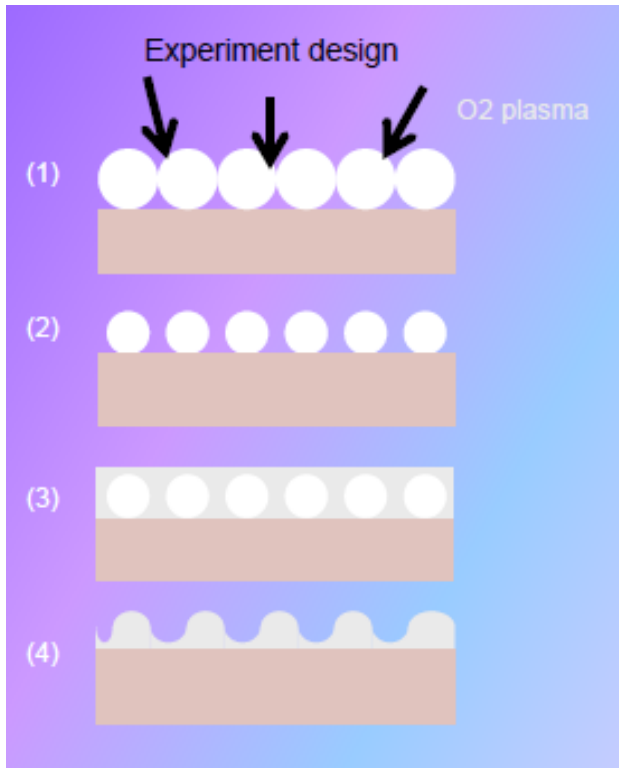
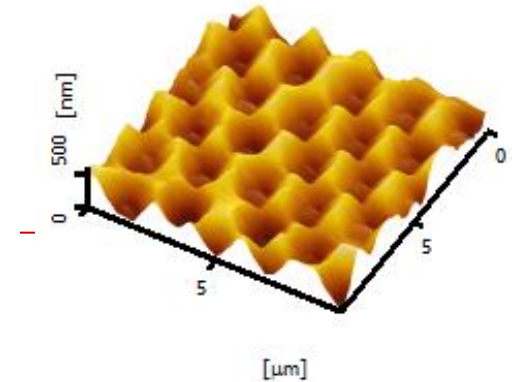
CWBR: conductive white
back reflector





● Reflection at the back side

- ✓ Random structure
- ✓ Periodic structure : Polystyrene spheres (PS)





2. Key issue: reduce cost

- High deposition rate
- High stable efficiency
- Single chamber deposition
- Suitable large area
-

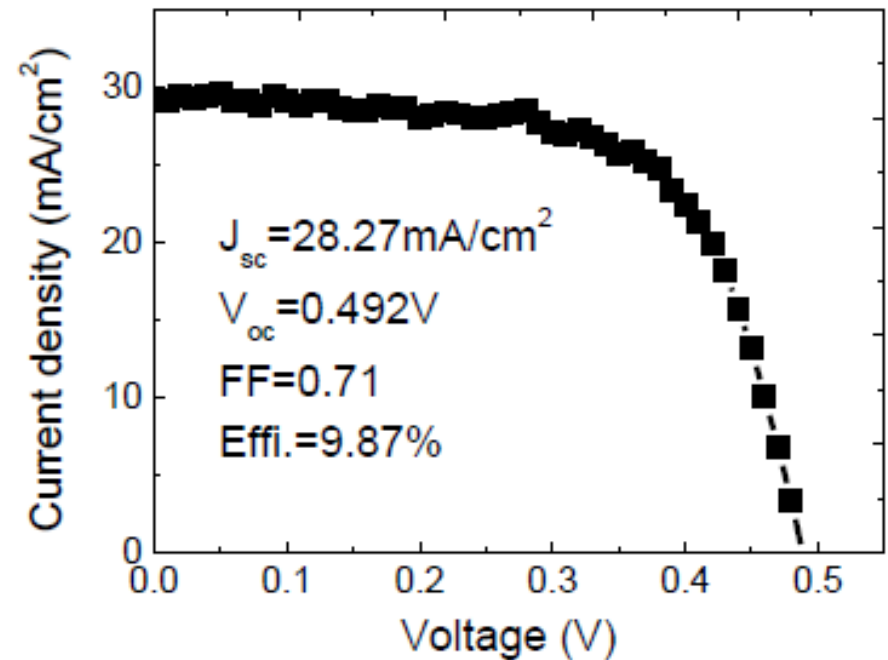
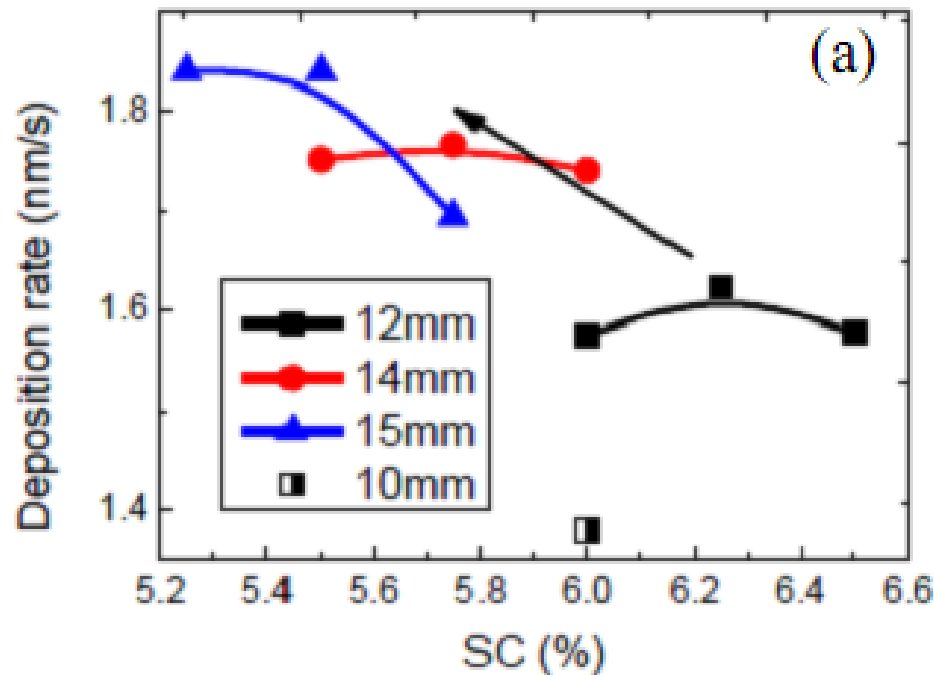


A: High deposition rate

- ◆ High pressure and high power (3Torr and 70W(powered electrode area: >100cm²))



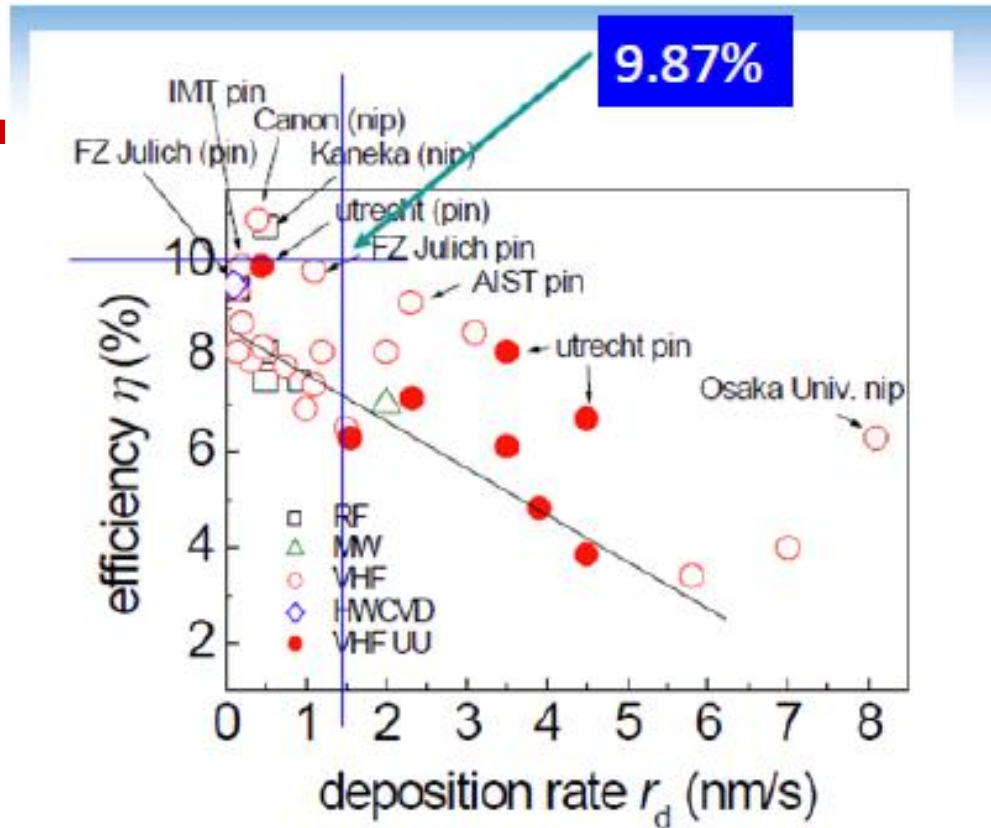
Home made



VHF-PECVD system



Microcrystalline silicon solar cell



Deposition rate: 1.5nm/s; Conversion efficiency: 9.87%



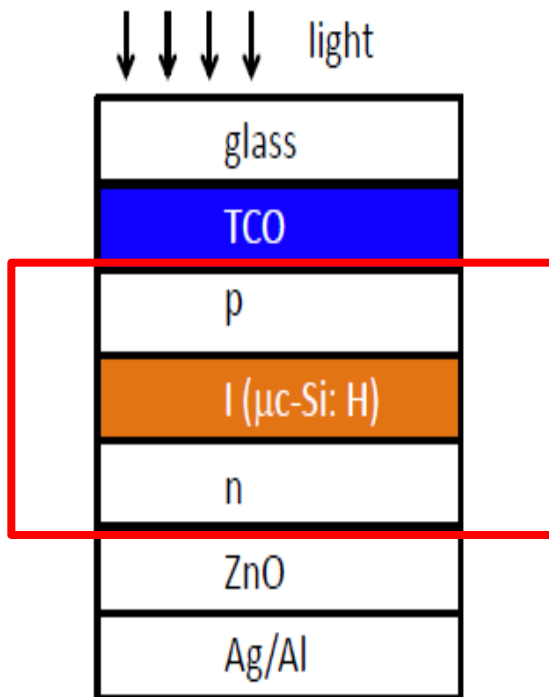
南开大学

Nankai University

Home made

B: Single chamber

◆ P, I, N deposited in a chamber

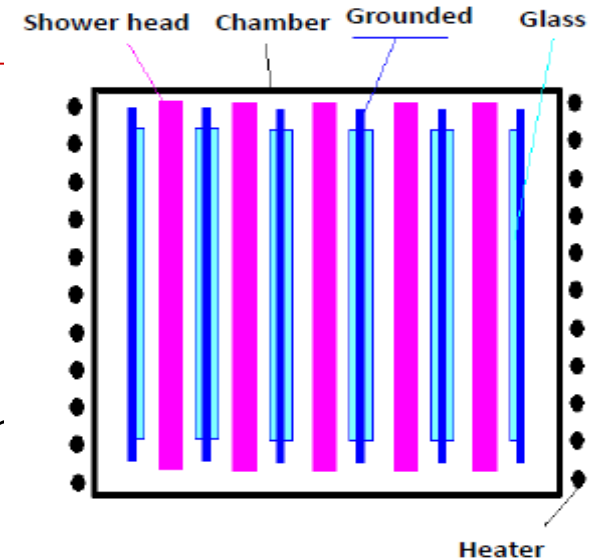


• Advantages

- High electrode utilization
- High gas utilization
- Easy operation and less servicing.

• Disadvantages

- Contamination-doping gas
- Serious for microcrystalline silicon





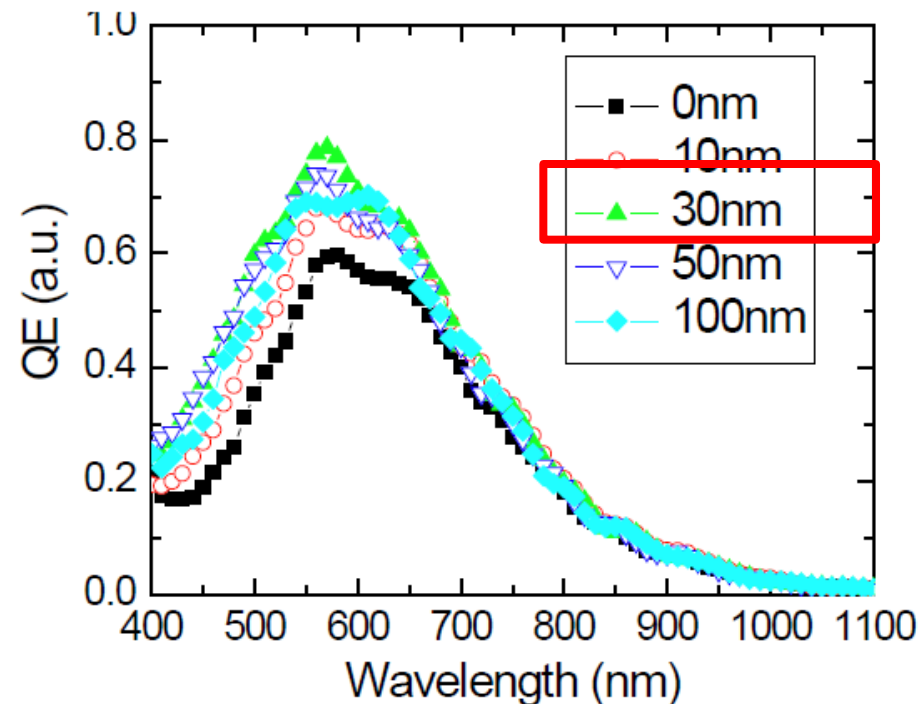
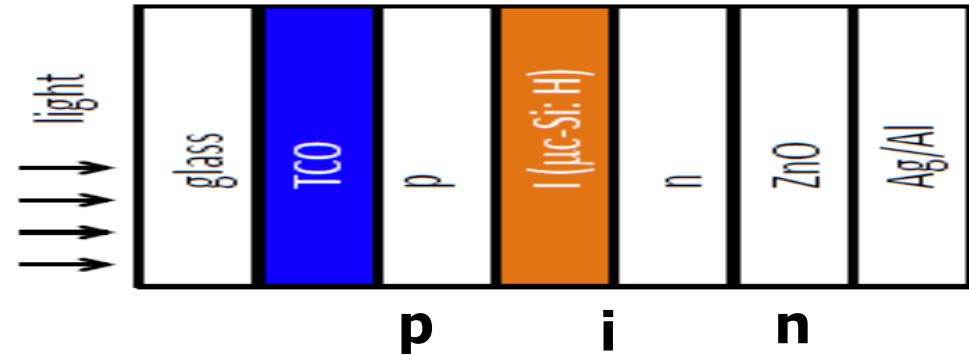
B: Single chamber

Boron contamination:

p/I interface

High Xc interface layer

- Improved short wavelength response
- Suitable thickness



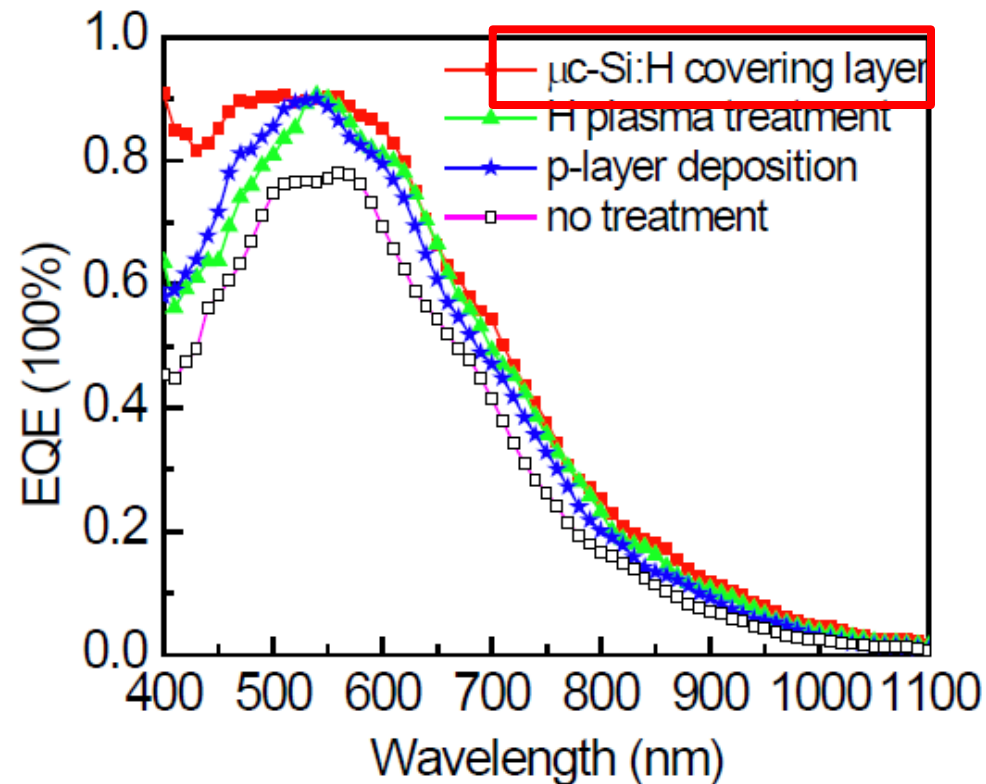
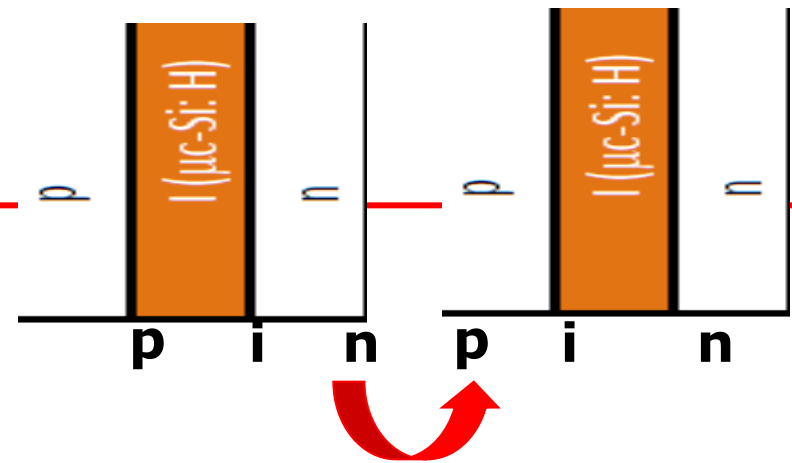


B: Single chamber

Phosphorus contamination:

n/p interface

- Improved short and long wavelength response
- The $\mu\text{c-Si:H}$ covering layer is the best method to reduce phosphorus contamination.





Nankai University (China)
a-Si/multi-Si Cell

a-Si/ μ c-Si tandem solar cells

Single chamber

Device ID: Cell A L1

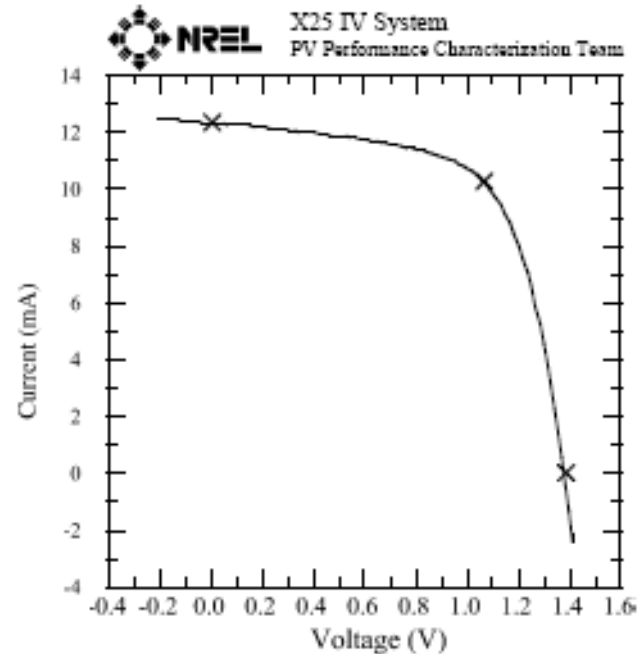
Jan 26, 2010 12:49

Spectrum: ASTM G173 global

Device Temperature: 30.0 ± 10.0 °C

Device Area: 1.027 cm^2

Irradiance: 1000.0 W/m^2



$V_{oc} = 1.3864 \text{ V}$

$J_{sc} = 12.289 \text{ mA/cm}^2$

$J_{sc} = 11.963 \text{ mA/cm}^2$

Fill Factor = 63.83 %

Fan used for cooling

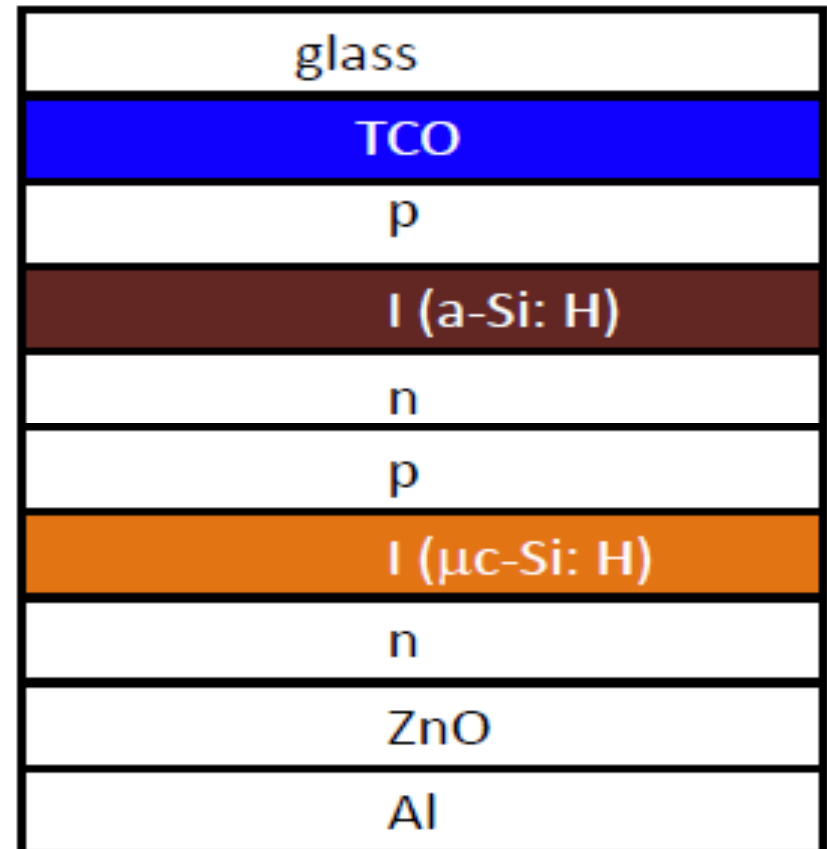
$I_{max} = 10.233 \text{ mA}$

$V_{max} = 1.0627 \text{ V}$

$P_{max} = 10.875 \text{ mW}$

Efficiency = 10.59 %

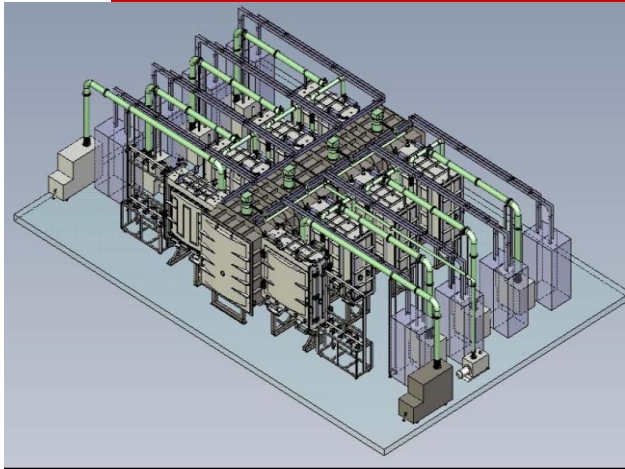
↓ ↓ ↓ ↓ light



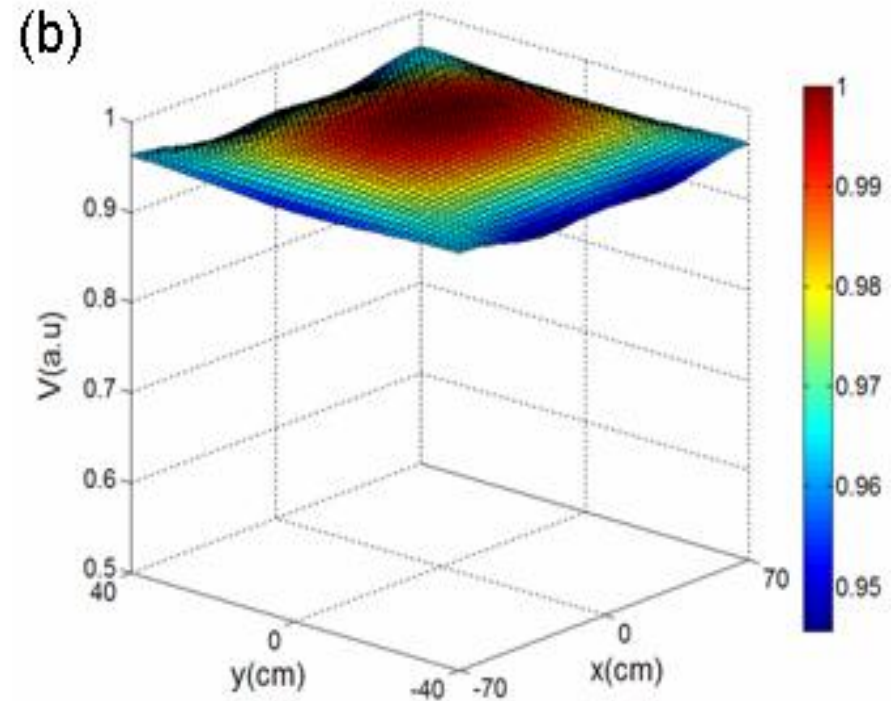
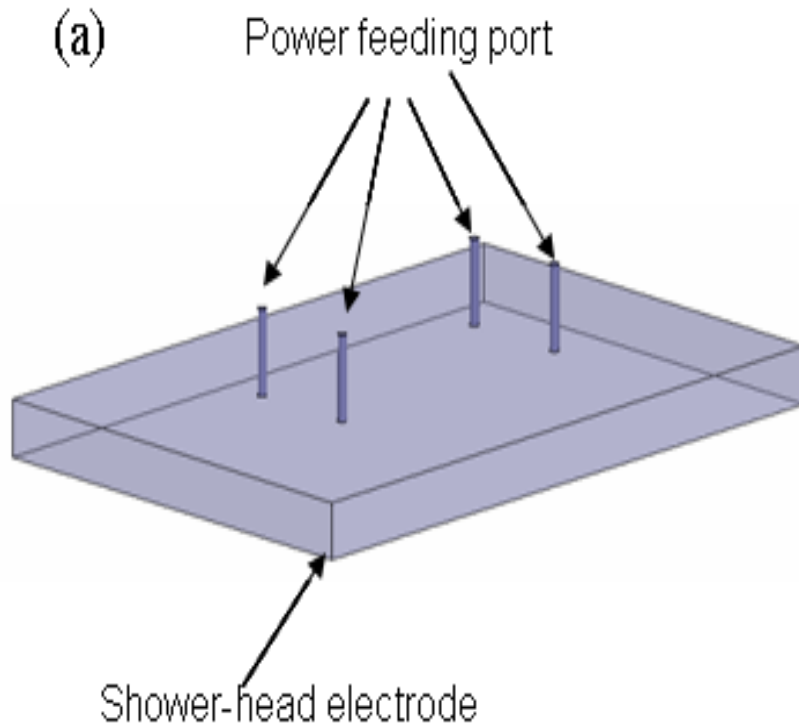


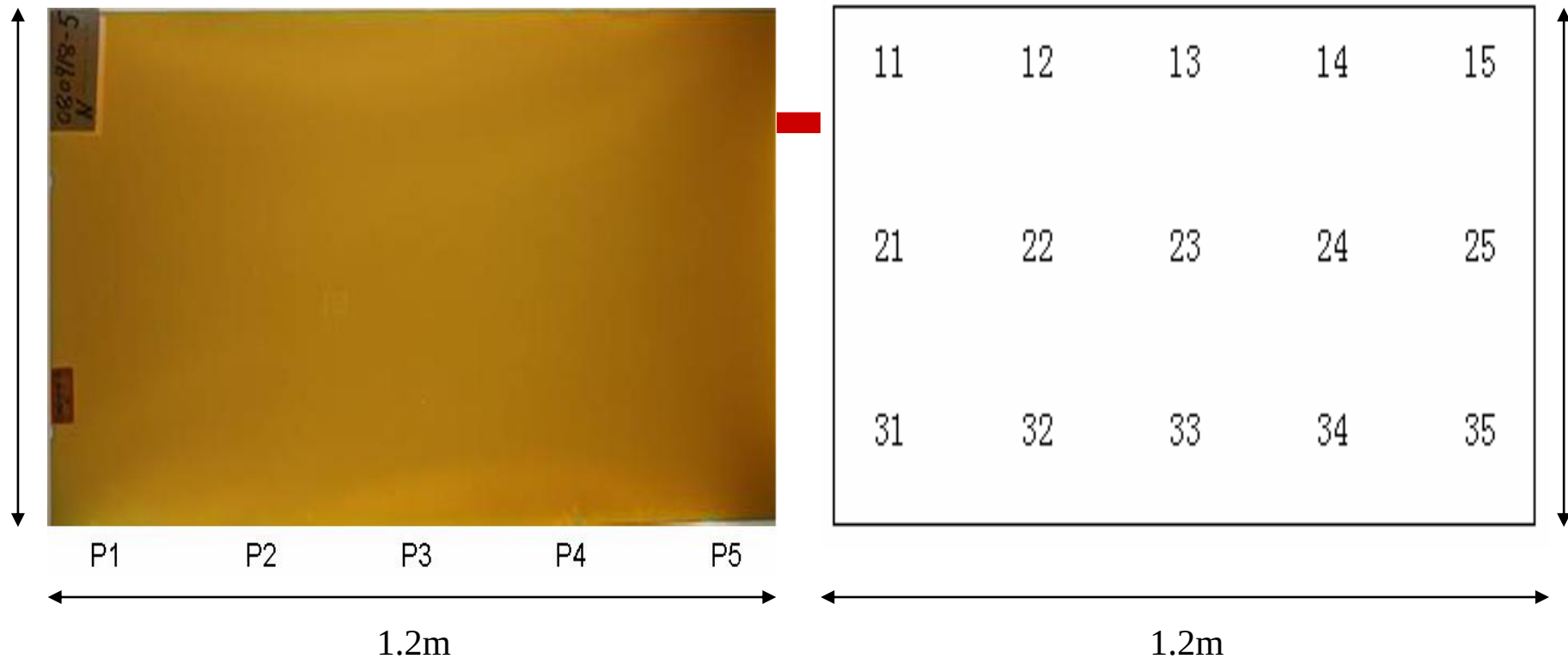
Large area:

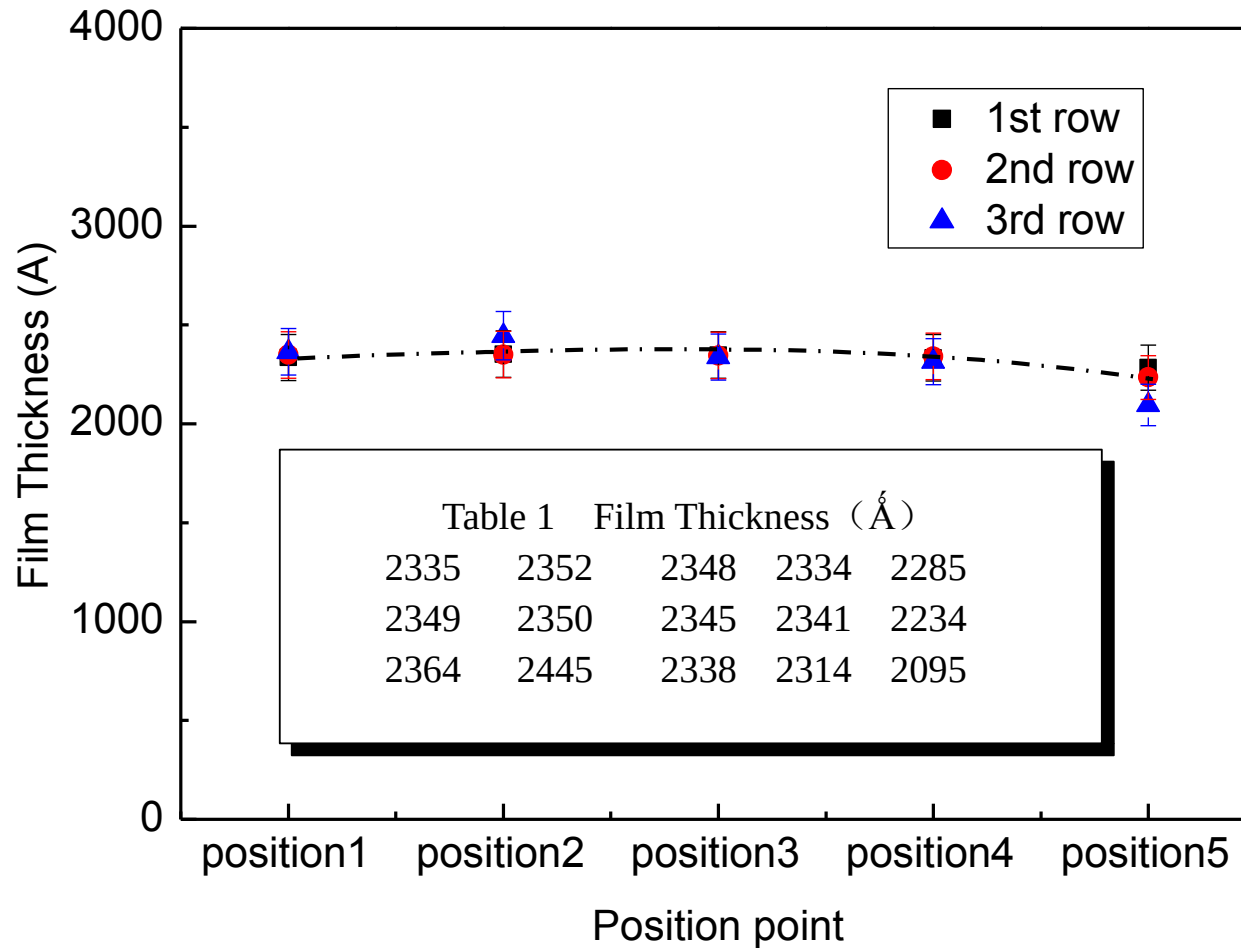
In 2011, developed a VHF-PECVD system with the capacity of 2MW/year .



- ◆ 8 chambers in this system;
- ◆ 40.68 MHz;
- ◆ substrate area is 2 feet by 4 feet;
- ◆ Each chamber simultaneously deposited two pieces.

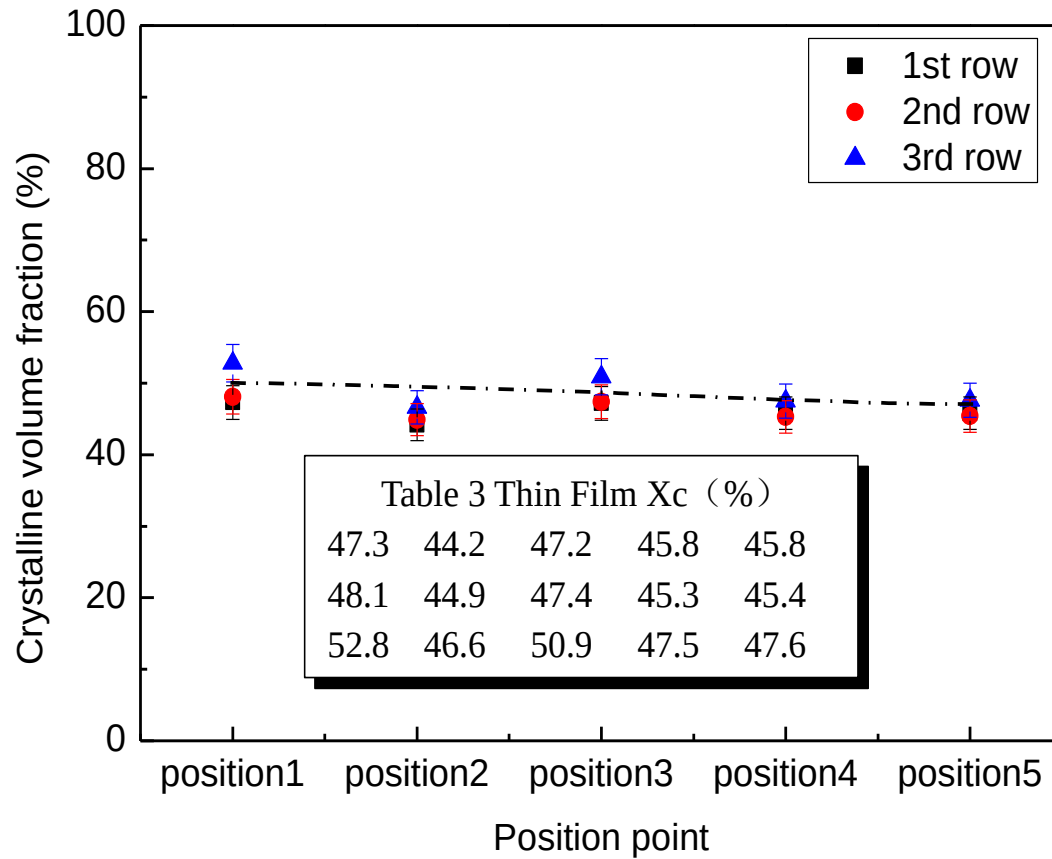






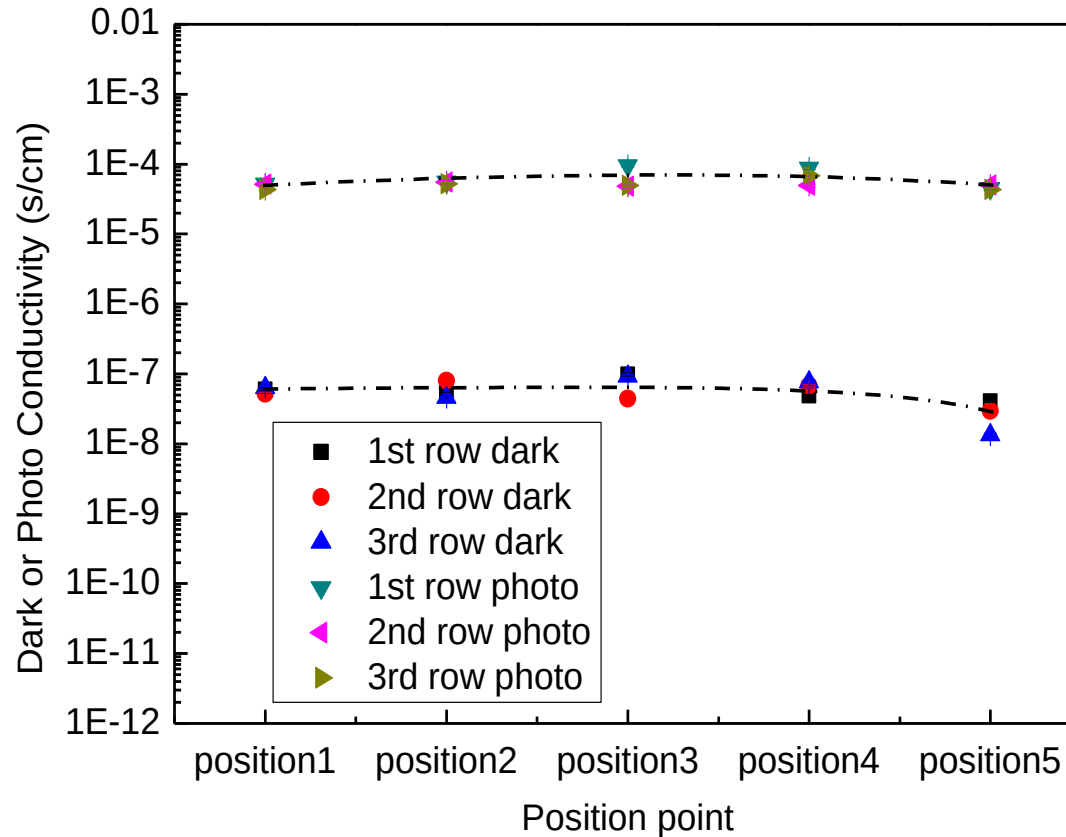
Un-uniformity for thickness:

Less than 3.85% was achieved at edge exclusion 2cm



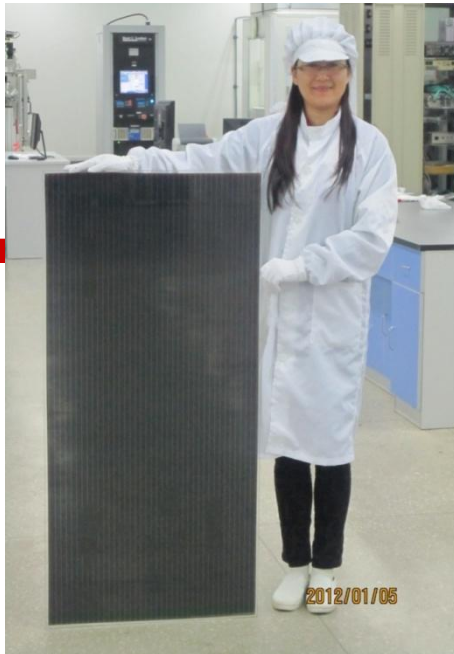
Un-uniformity for X_c:

Less than 4.8% was achieved at edge exclusion 2cm

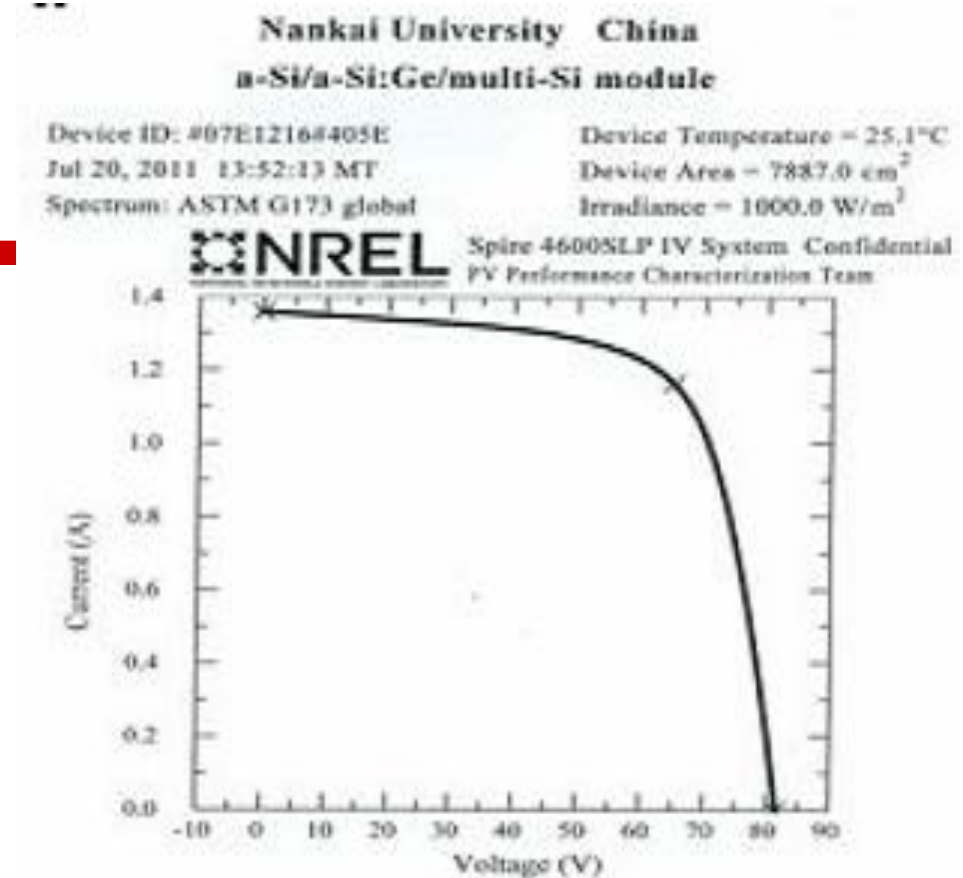


Un-uniformity for electrical properties:

Dark conductivity: 10^{-8} S/cm; Photosensitivity: ~ 1000



13KW a-Si/a-SiGe/ μ c-Si solar
module PV station



$V_{oc} = 81.51$ V

$V_{max} = 64.98$ V

$I_{sc} = 1.359$ A

$I_{max} = 1.163$ A

Fill Factor = 68.3%

$P_{max} = 75.60$ W

Efficiency = 9.59%

Device Dimensions = 124.4 x 63.4 cm

I_{sc} to V_{oc} 100 x 40 Jbox west, Property of NREL, Top cell,



Summary

◆ Improving efficiency

- **New Materials**

- **Light management**

- ✓ ZnO NW ARC
- ✓ Innovative front electrode
- ✓ Back reflector

◆ Low Cost technique

- High initial conversion efficiency 12.39% for a micromorph tandem cell;
- Single chamber-deposited tandem solar cells with an efficiency of 10.59%;
- Triple-junction module has achieved at 9.59% (NREL, 0.79m²) and increased by 20% compared to commercial module.



Future research directions----thin film silicon

Light management: (Suitable for other solar cells)

- External ARC and low absorption TCOs
- 2-D or 3-D photonic crystals (PC) based flat substrates

New materials :

- Silicon based alloys with O, C, and Ge

Performance ($\eta > 20\%$):

- Increase Voc (growth on flat substrates)



南开大学
Nankai University

Institute of photo-electronics thin film
devices and technique

Acknowledgements !

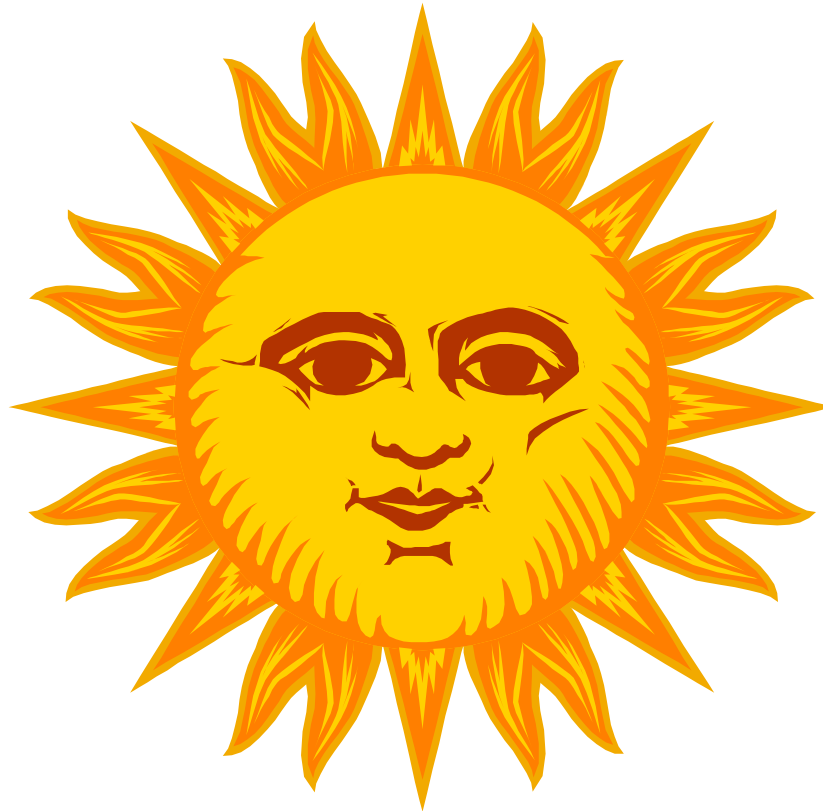


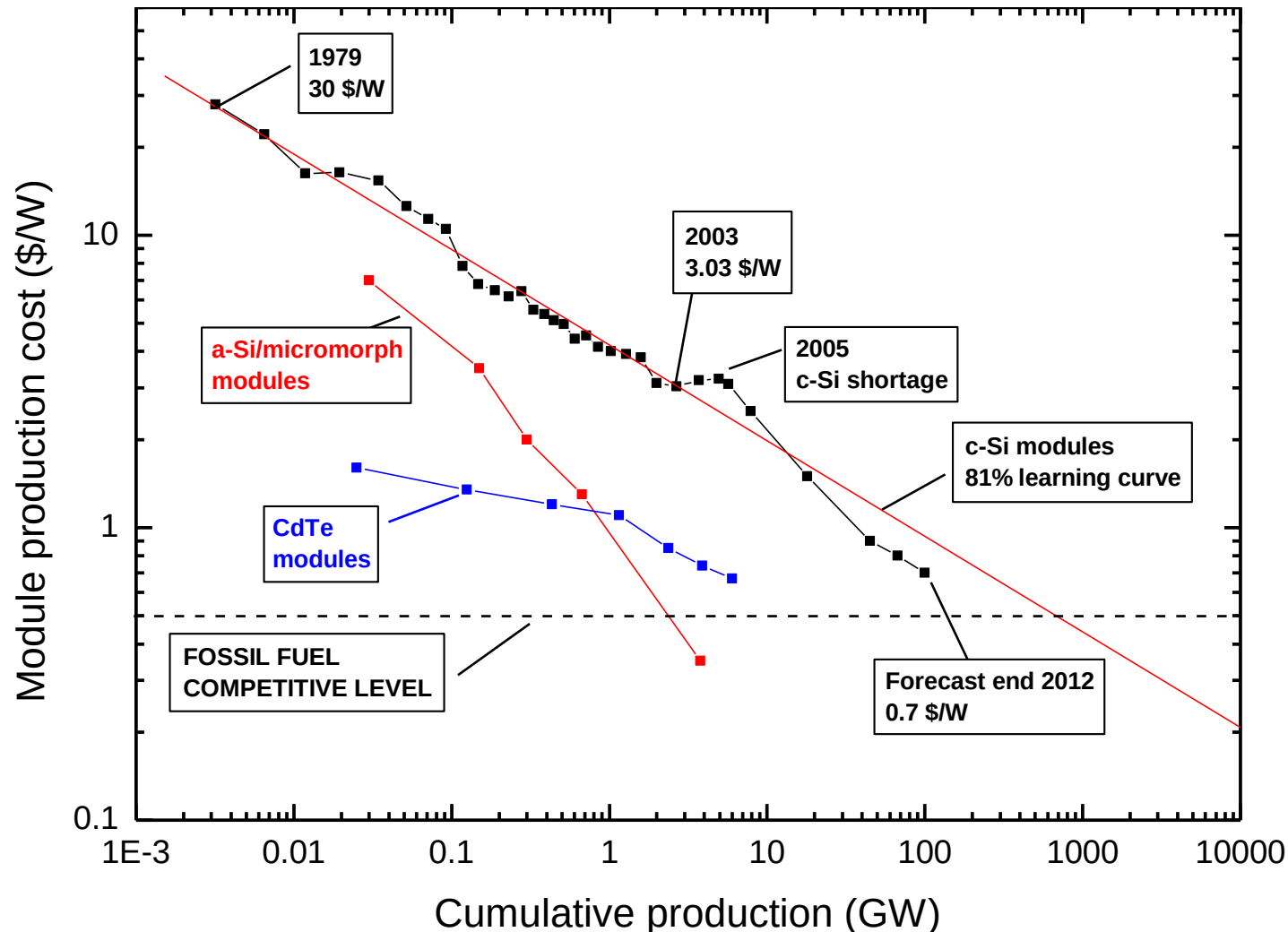


南开大学
Nankai University

Institute of photo-electronics thin film
devices and technique

Thank you for your attention !





Production costs:

C-Si (lower limit):
0.8 \$/W $\approx$ 0.6 €/W
Eff $\approx$ 15 %

CdTe (First Solar):
0.67 \$/W $\approx$ 0.51 €/W
Eff = 12.2 %

a-Si:H/mcSi
(Oerlikon, ThinFab14
0):
0.35 \$/W $\approx$ 0.27 €/W
Eff = 10.8 %

CIGS (Manz AG)
0.55 \$/W $\approx$ 0.42 €/W
Eff = 12.6% (Solar
Frontier)



南开大学

Nankai University

**Institute of photo-electronics thin film
devices and technique**





南开大学

Nankai University

**Institute of photo-electronics thin film
devices and technique**

